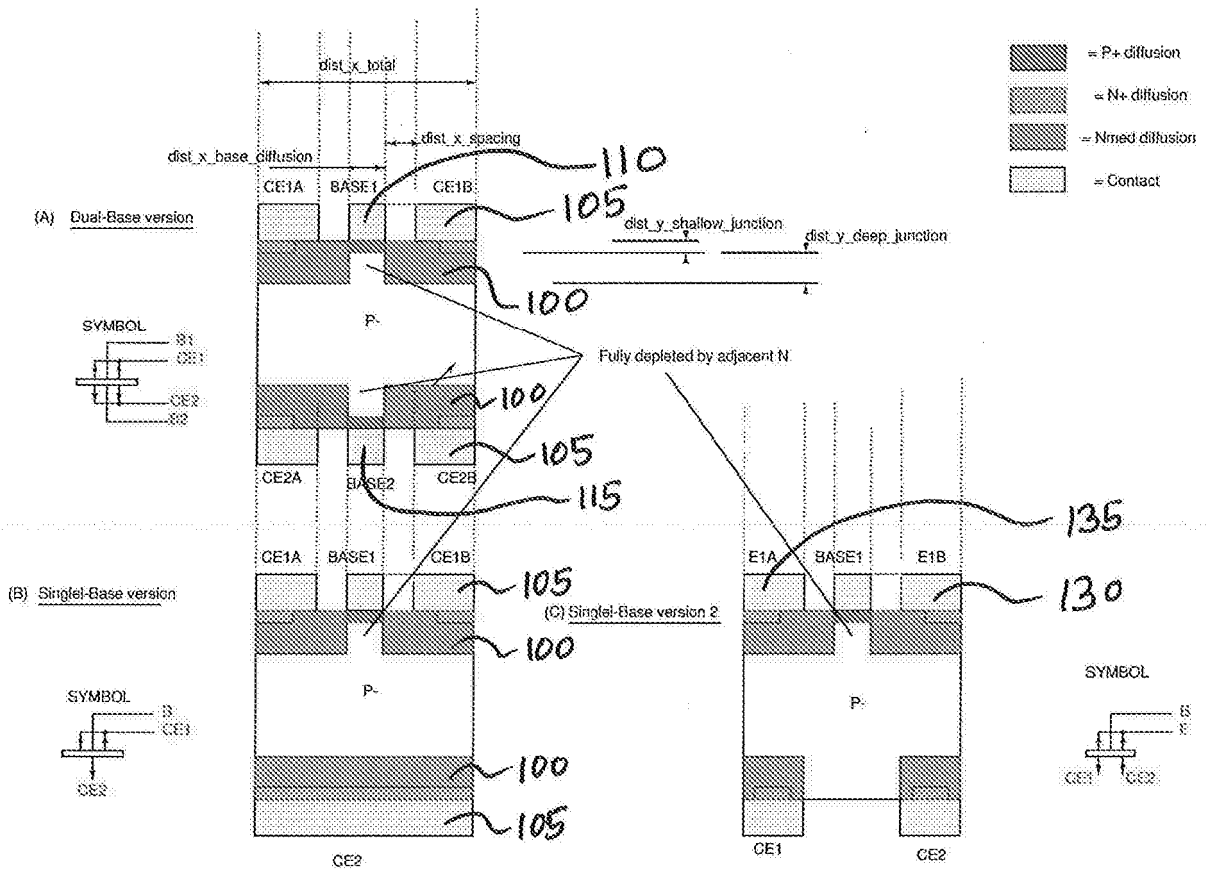


FIG1

(1 of N)



(2 of N)

FIG2a - Test Circuit

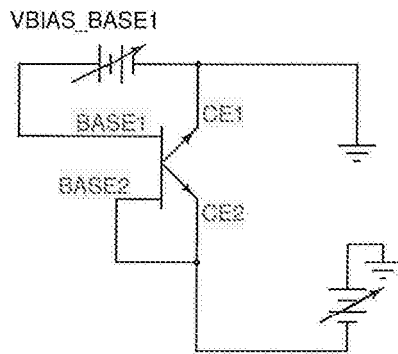


Fig2c Power scavenging concept

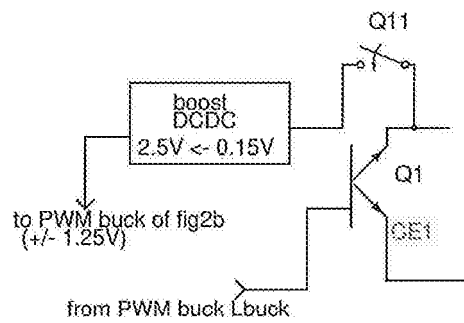


FIG2b - Intelligent Drive circuit

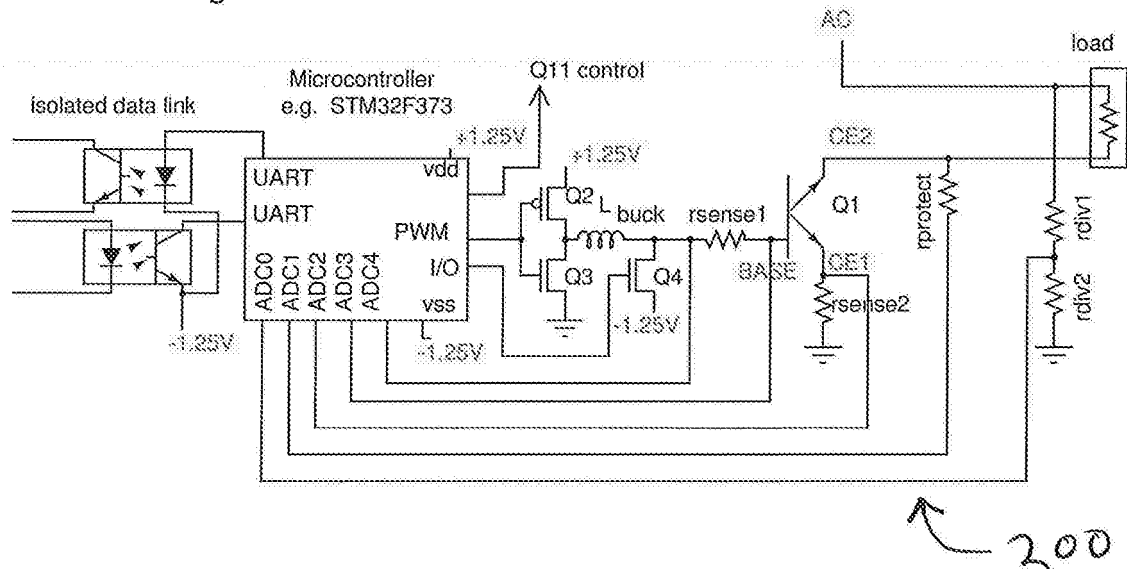


Fig 3a, Hole current density at 0.6V Vbe - top base driven only

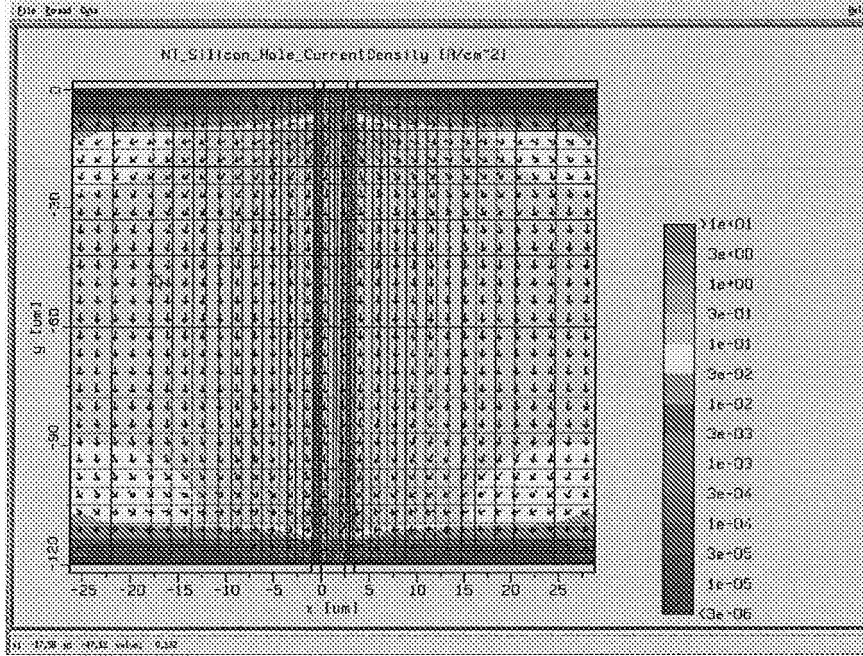


Fig 3b, Electron current density at 0.6V Vbe - top base driven only

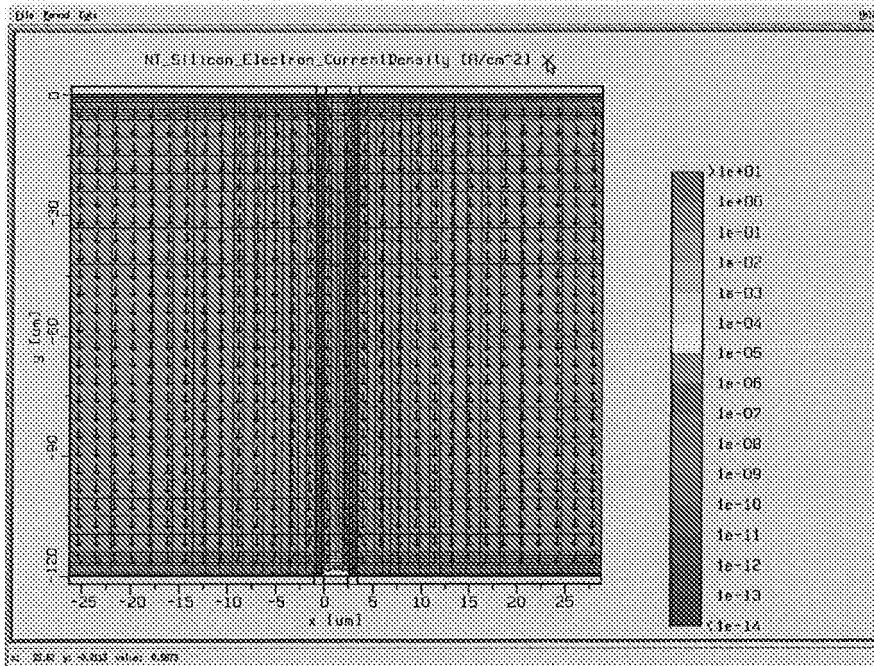


Fig4a

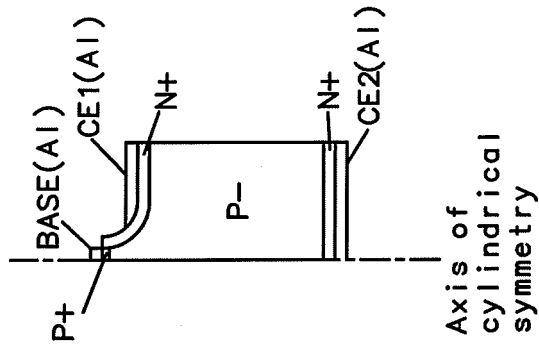


Fig4b

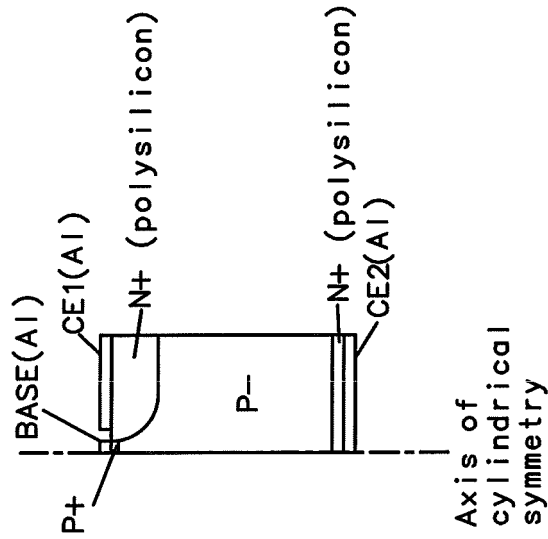
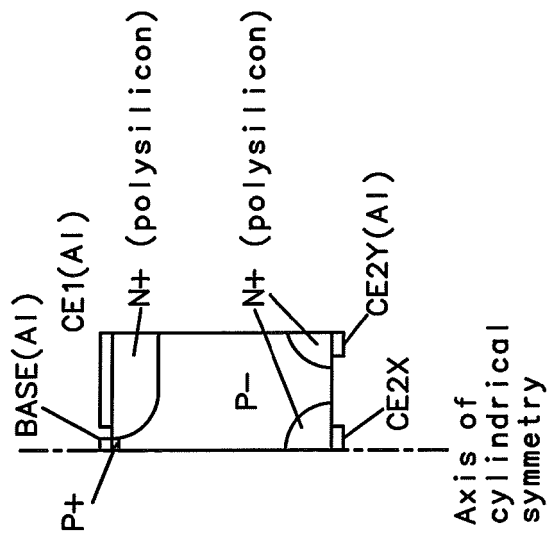


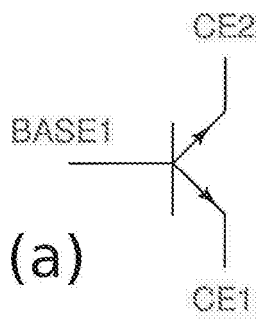
Fig4c



AI = aluminium

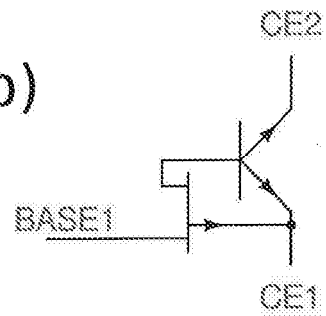
FIG5

SYMBOL



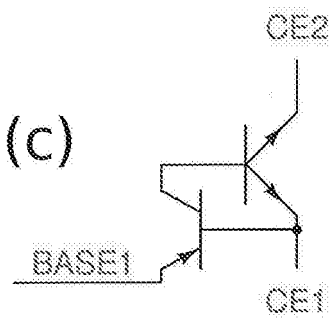
EQUIVALENT CIRCUIT

(b)



non-encroachment of donors in channel

(c)



encroachment of donors in channel

FIG6

Additional circuits for power scavenging

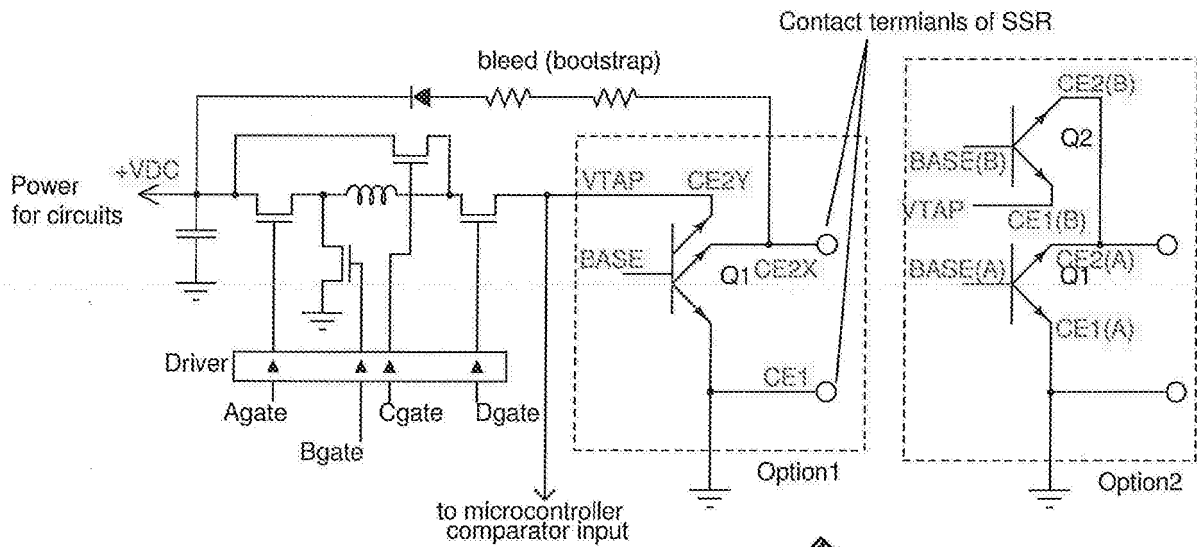


Fig 7

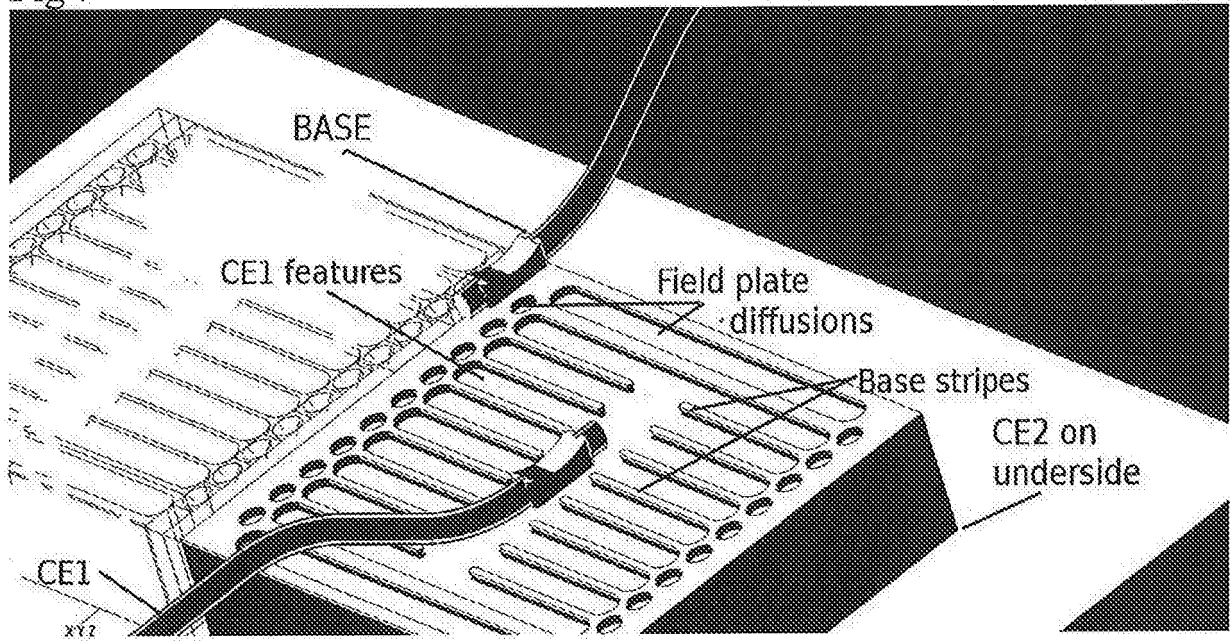


Fig8

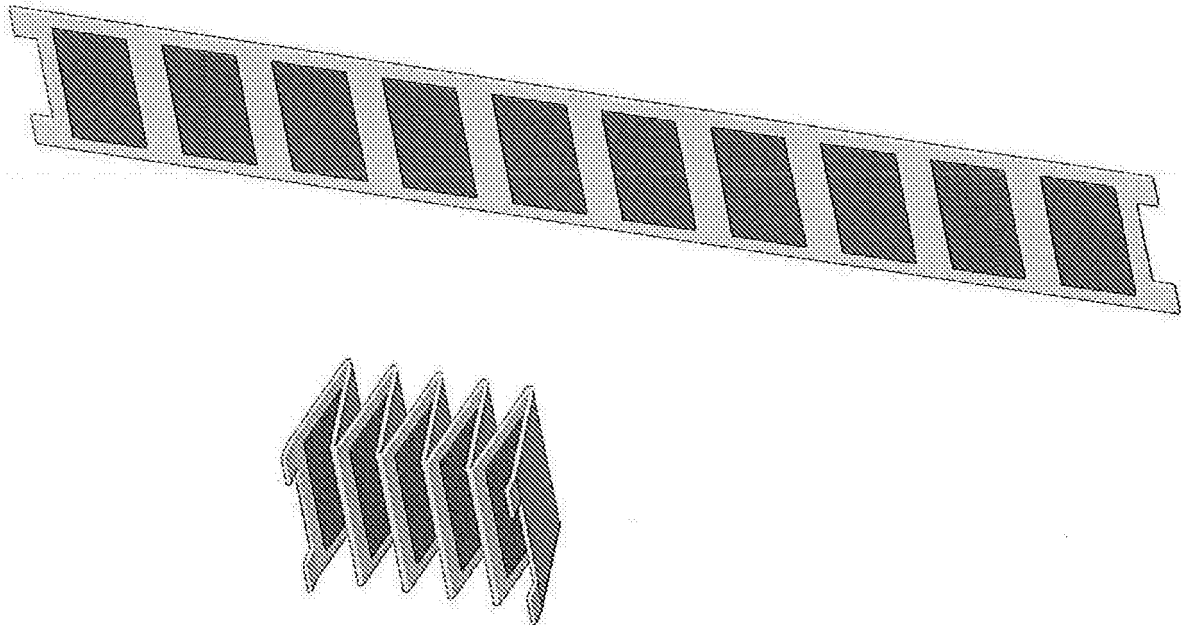


Fig 9

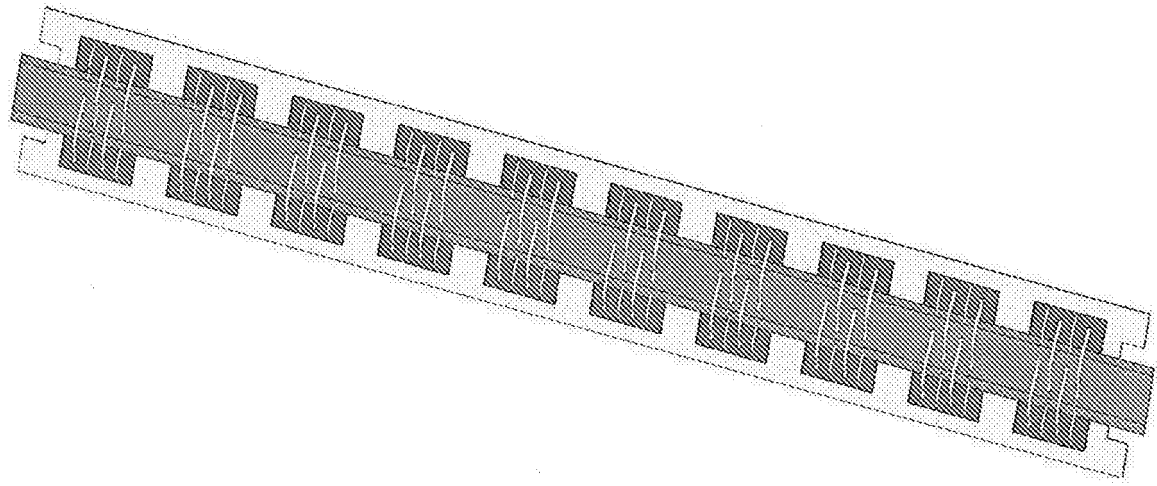
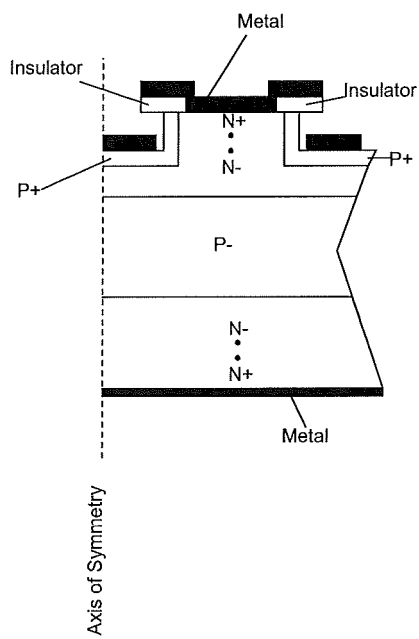
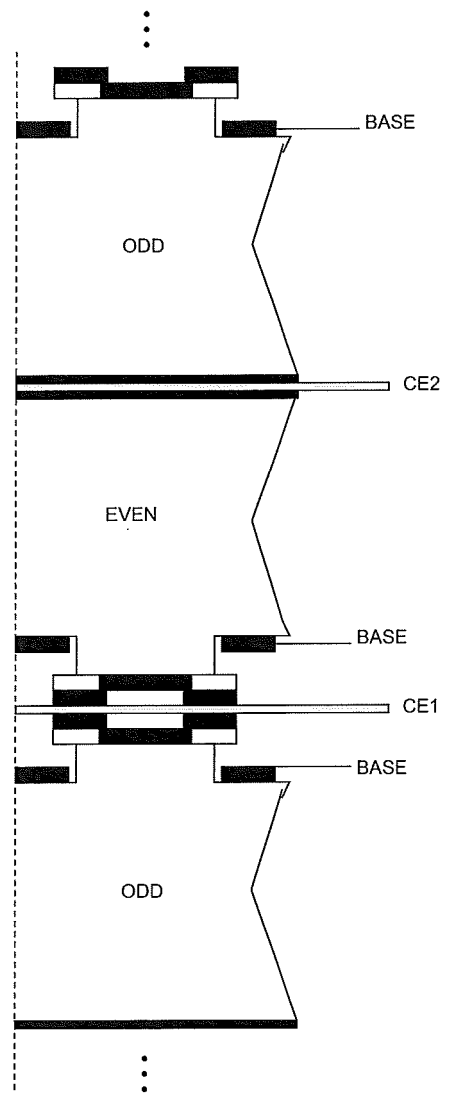


FIG10. Recessed 'BASE' PNP base version (9 of N)



(a) Unit design. Cylindrical symmetry



(b) Stacked design for higher current or higher voltage

Fig11

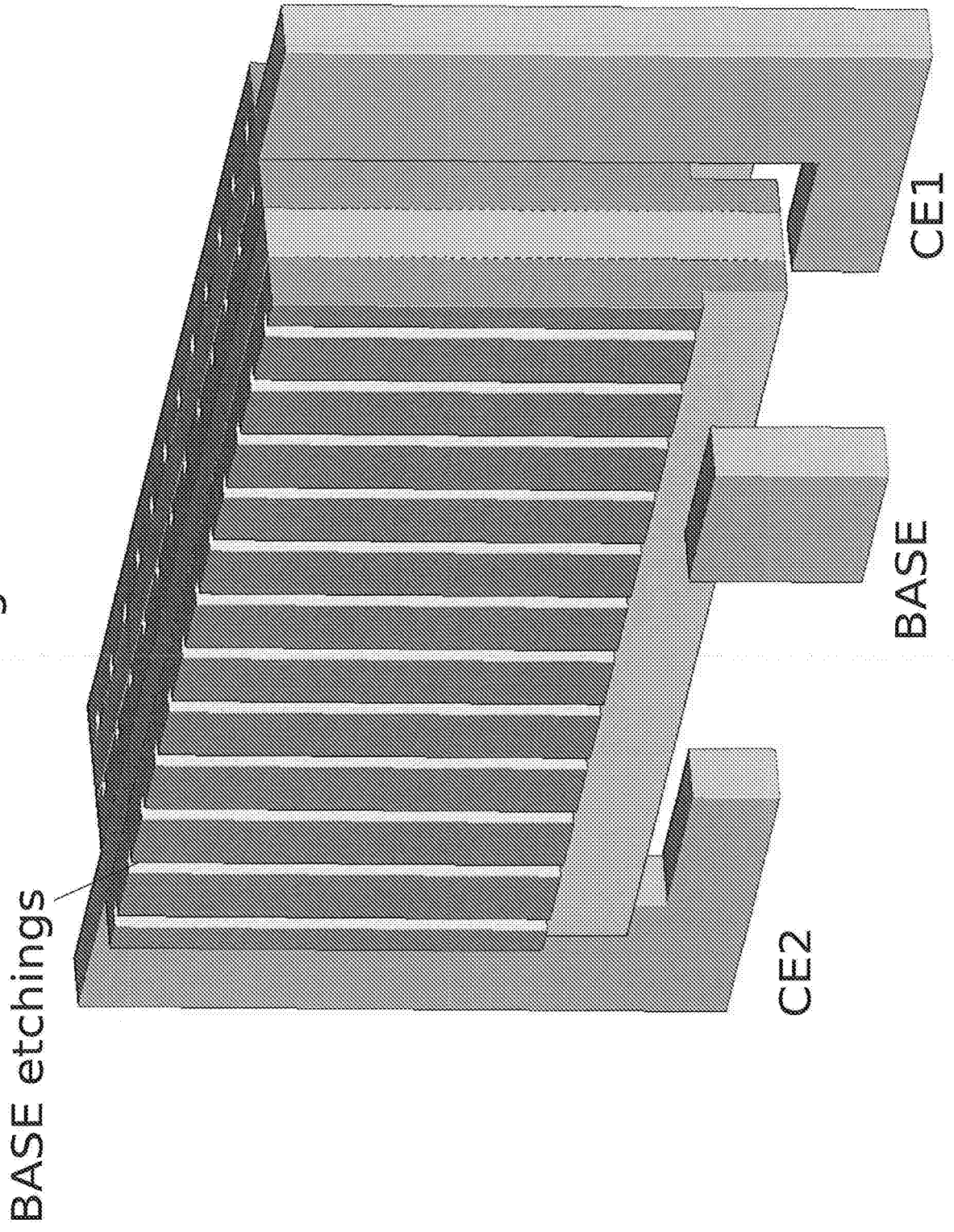


Fig12

Additional Modules tapped in

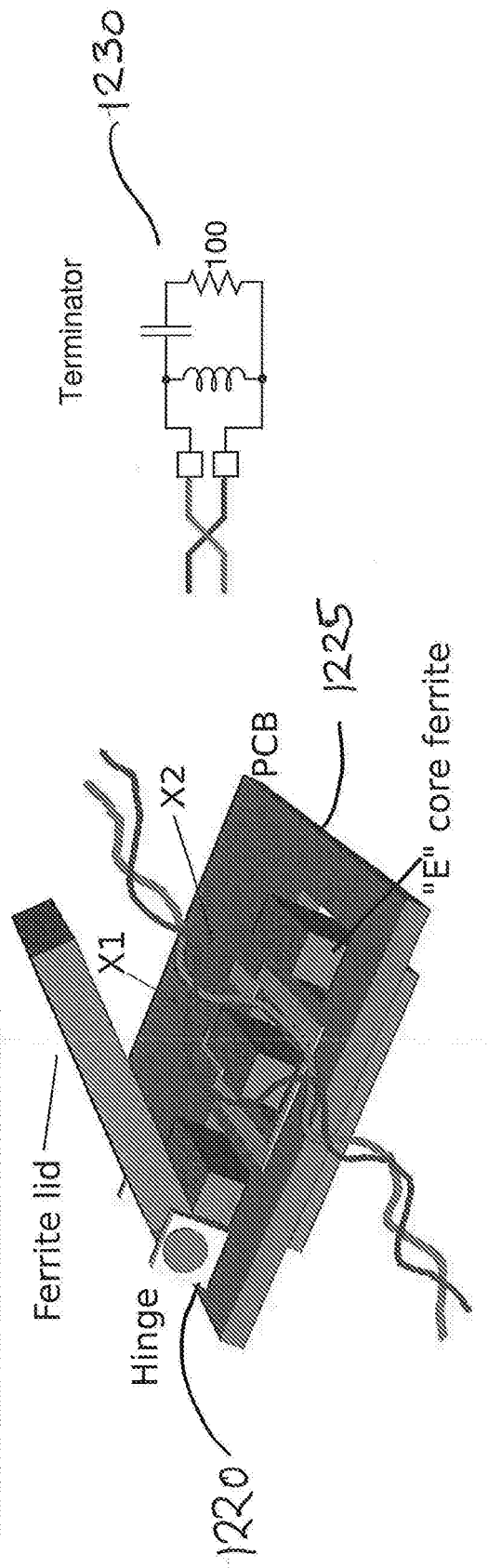
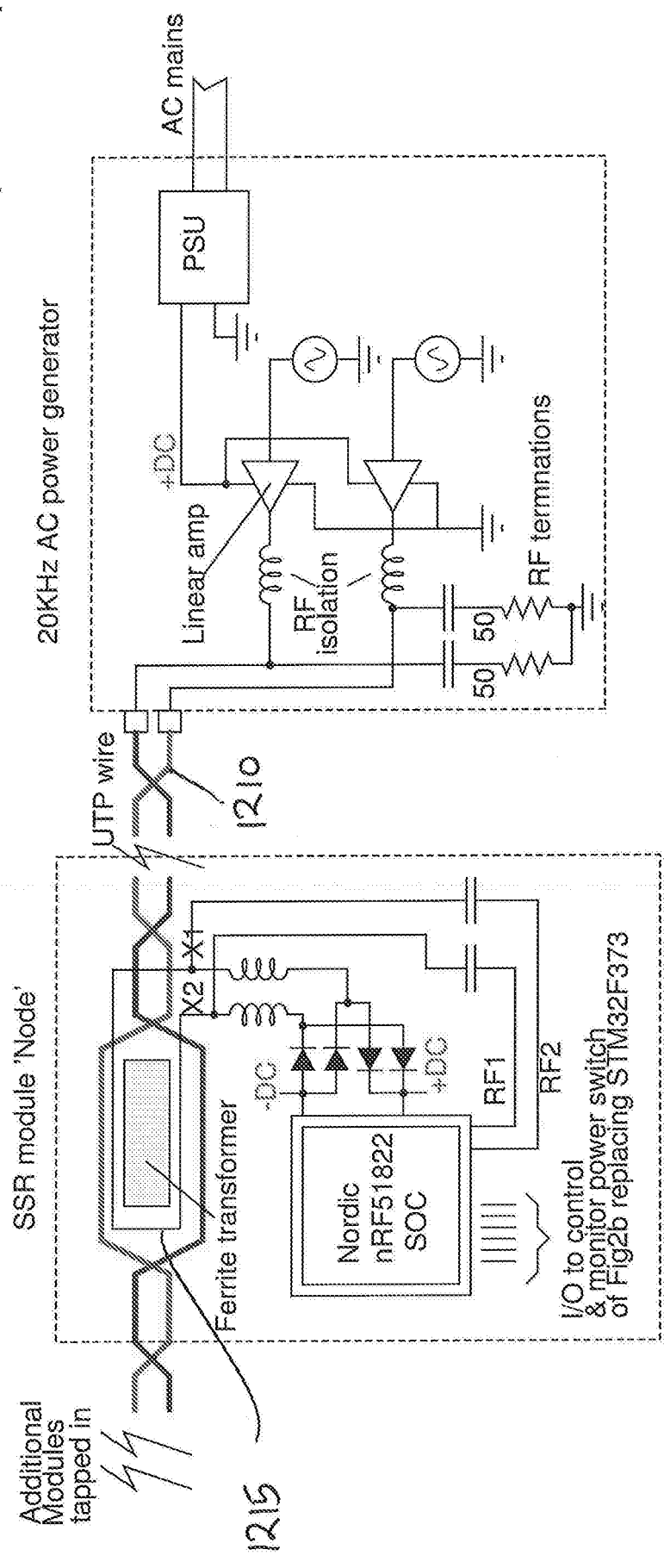
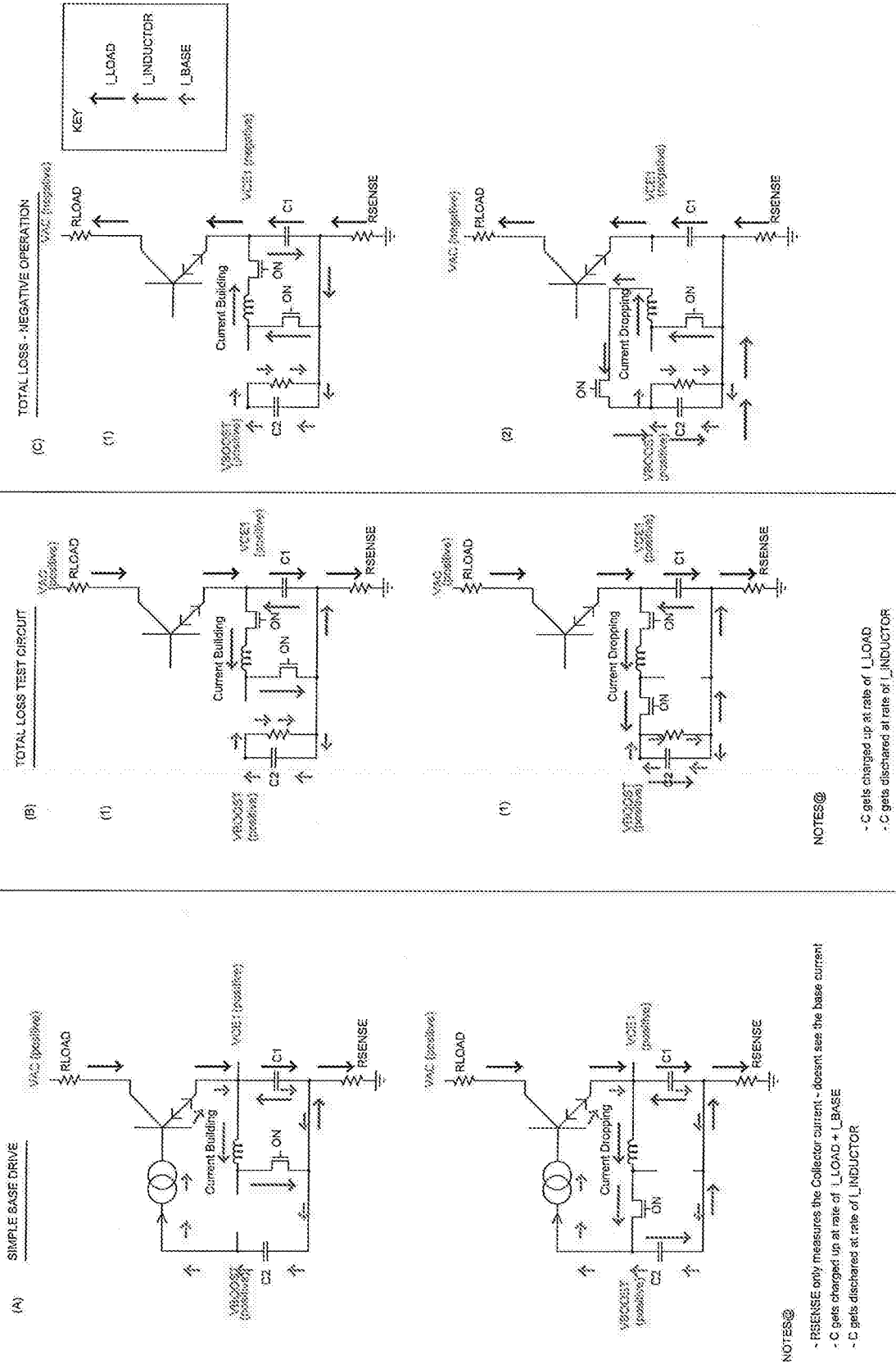


FIG13



NOTES@

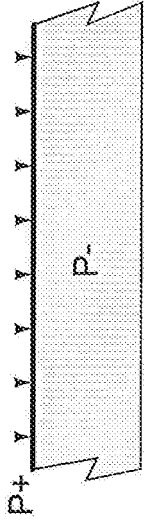
- RSENSE only measures the Collector current - dont see the base current
- C gets charged up at rate of $I_{LOAD} + I_{BASE}$
- C gets discharged at rate of $I_{INDUCTOR}$

NOTES@

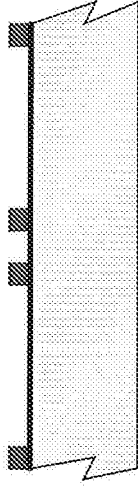
- C gets charged up at rate of I_{LOAD}
- C gets discharged at rate of $I_{INDUCTOR}$

Fig.14 - PROCESS STEPS for T2-JFET-base Transistor using Nitride

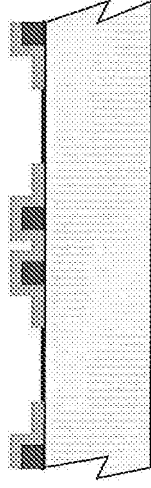
1) Boron Implant (optional)



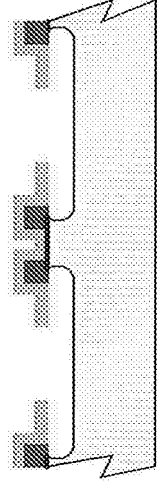
2) SiO2 Pattern



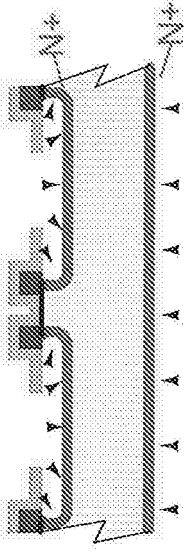
3) Nitride Pattern



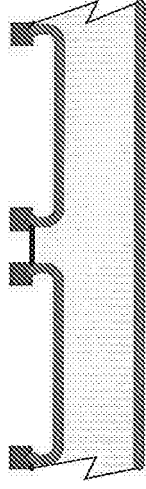
4) Wet (or dry) silicon Etch



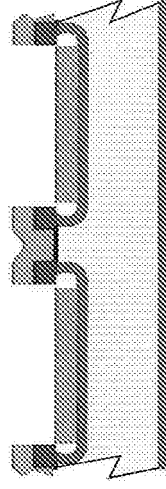
5) Phosphorous Diffusion



6) Nitride Strip



7) Metal Evaporation (self masking)



8) Finished device

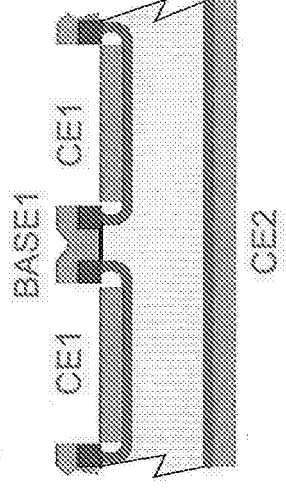


Fig.15 - PROCESS STEPS for T2-JFET-base using Oxide only

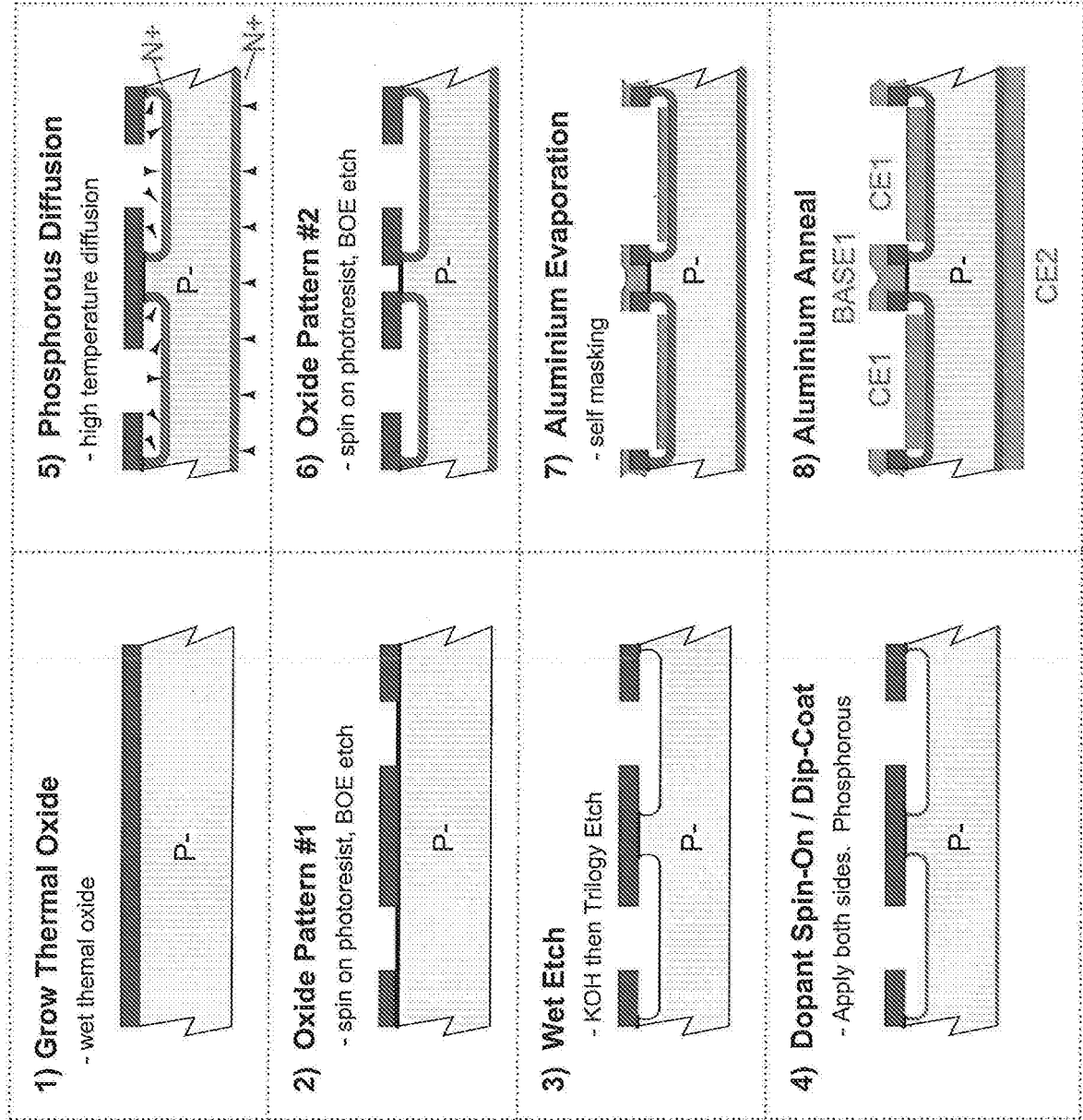


Fig. 16 - PROCESS STEPS for T2 - BJT base using oxide only

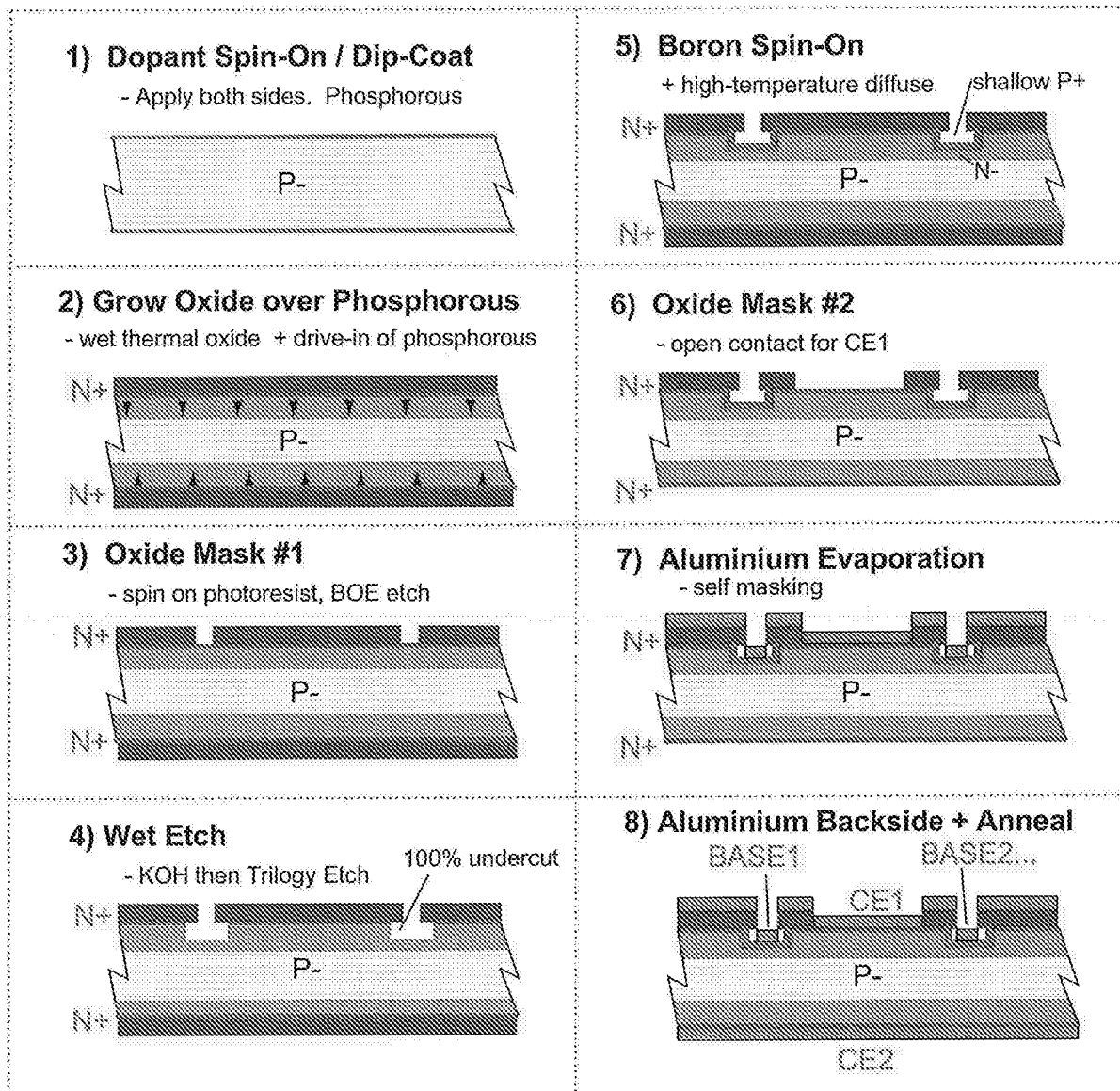


Fig. 17 - SINGLE MASK, T2-BJT base, <100> and <110> etching method

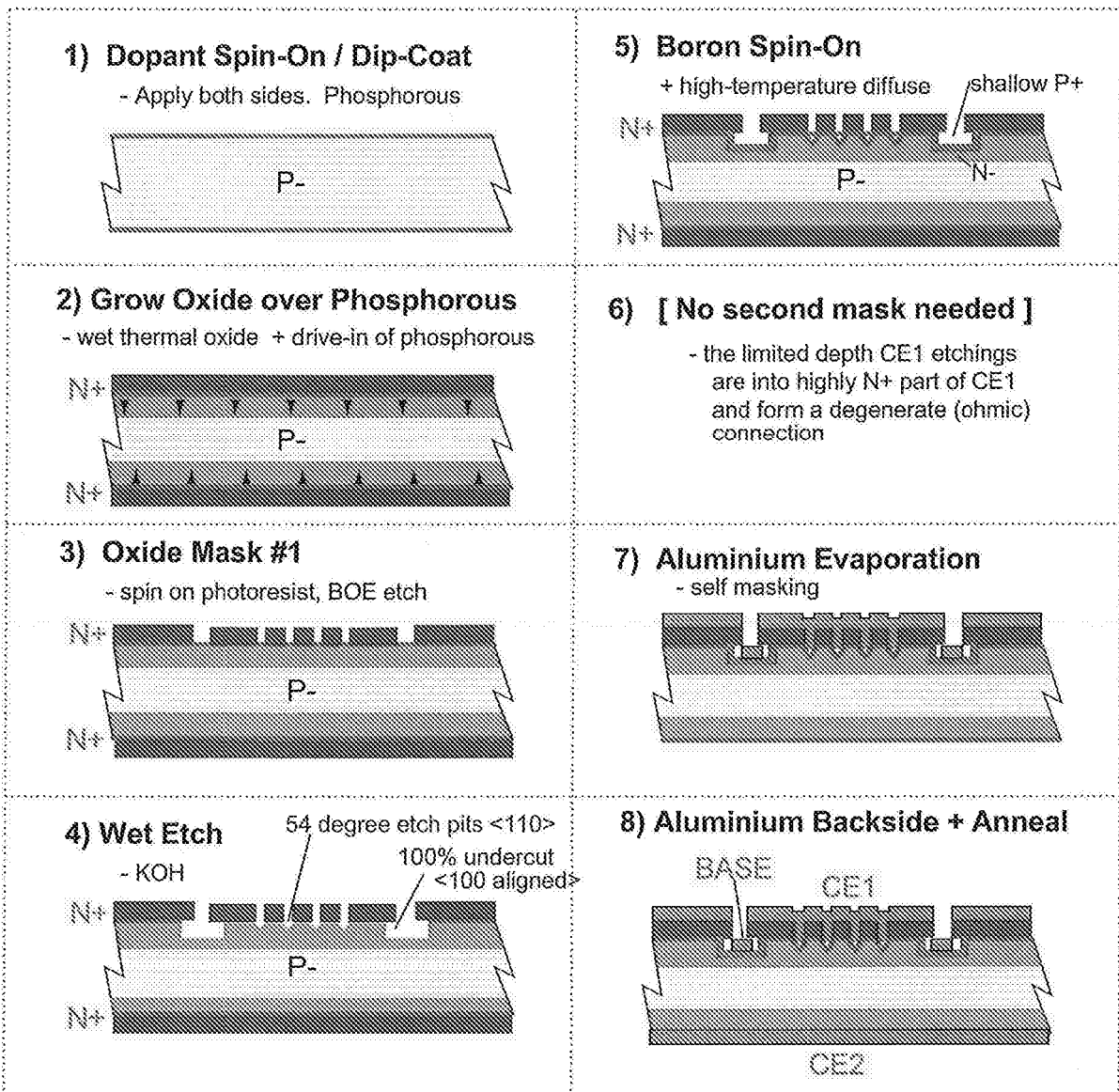


Fig. 18

Single Mask Scheme - with self-limiting contact depth but unrestricted trench depth using crystallographic anisotropic etch (KOH, TMAH, EDP or similar)

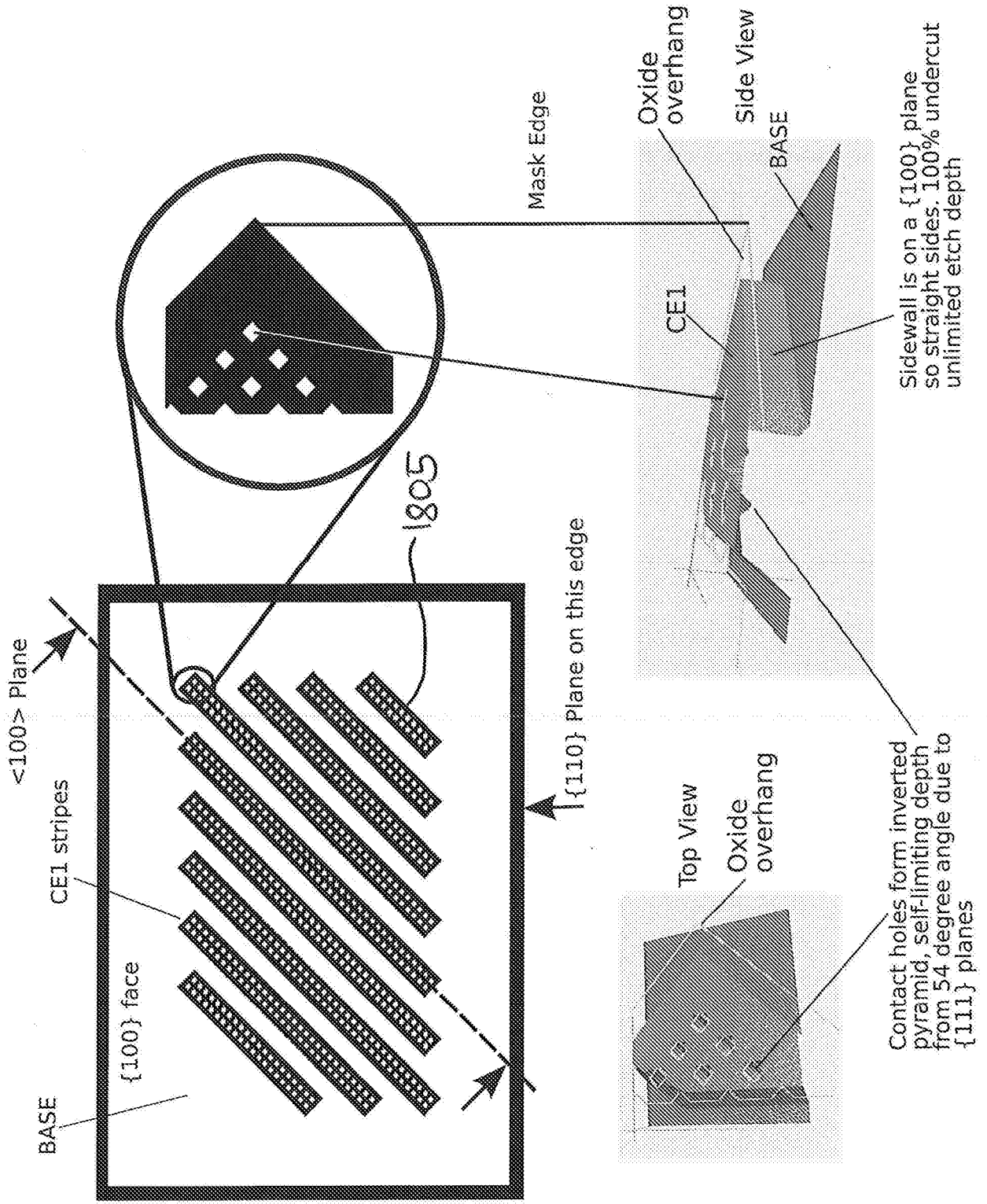
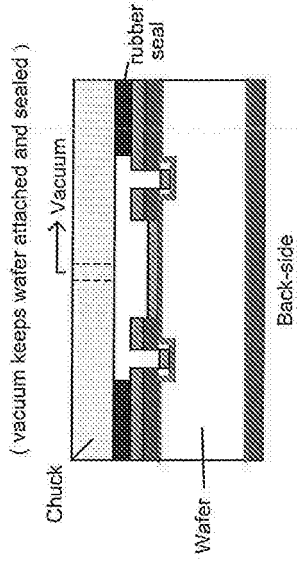
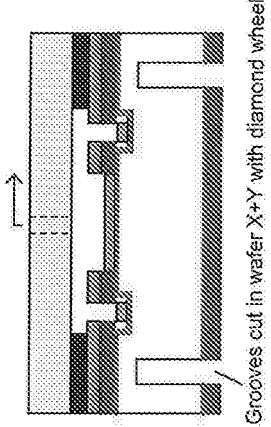


Fig.19 - SINGULATION / BEVEL / PASSIVATION STEPS for THYRISTOR 2.0

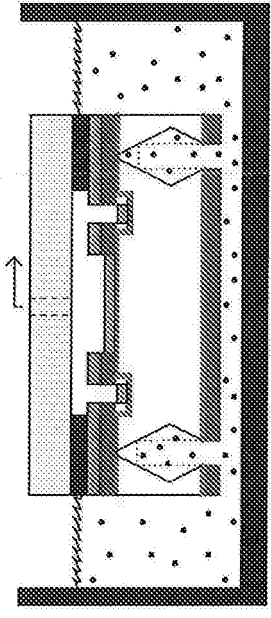
9) Mount wafer on holder



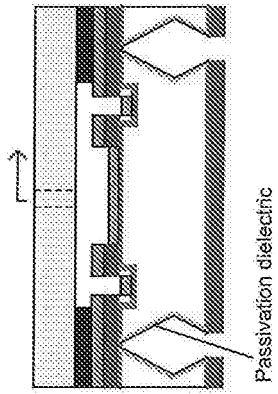
10) Grind singulation slots (X and Y)



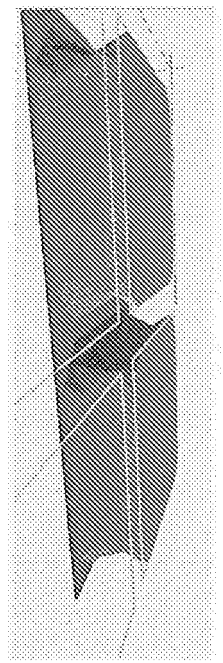
11) Anisotropic Wet Etch (e.g. KOH solution)

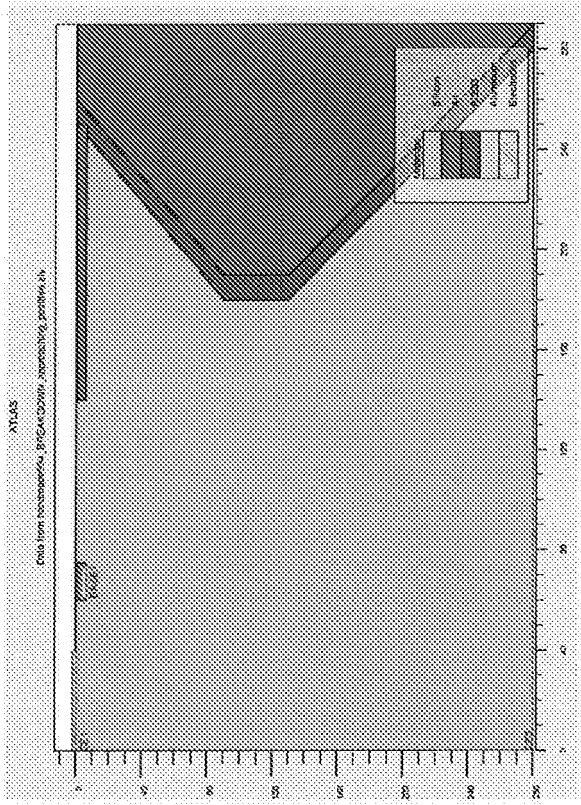


11) Passivation (CVD or ALD) Al2O3

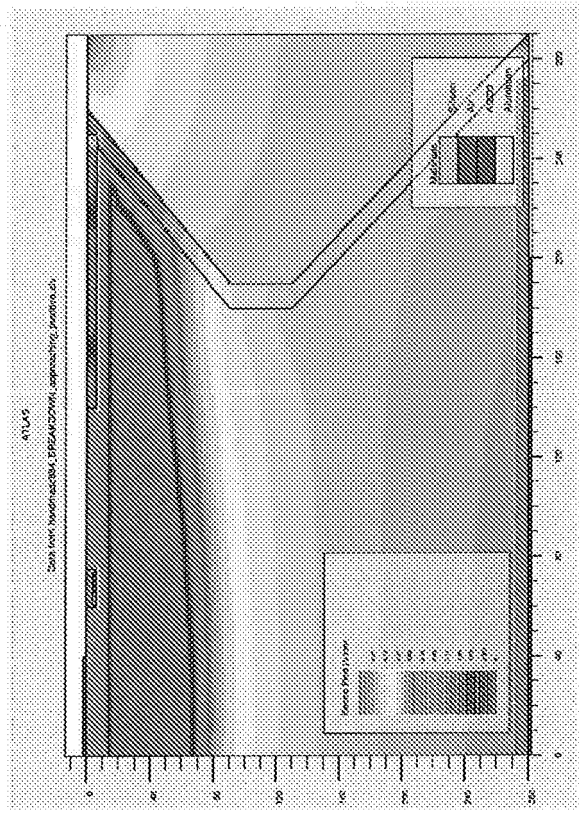


Simulation of above using wet-etch atomistic simulator



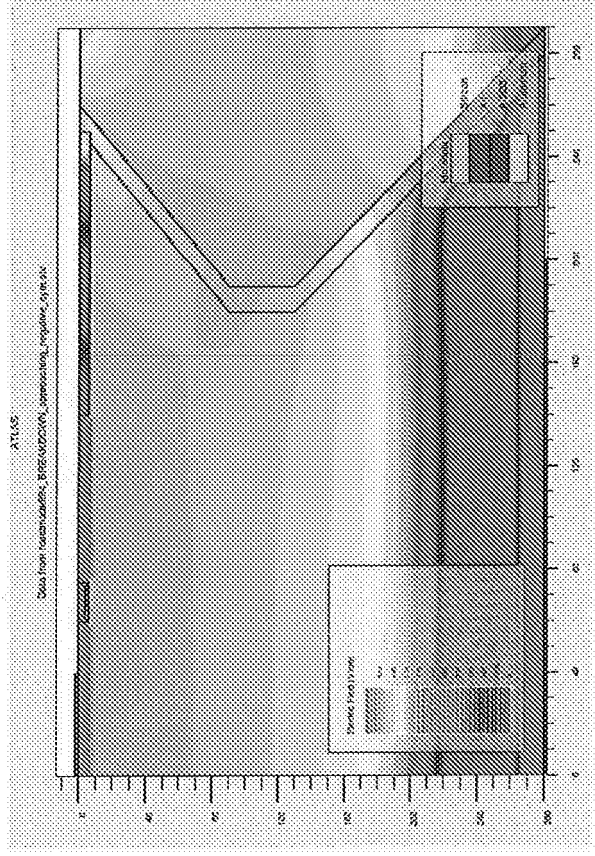


Double Positive Edge layout



CE2 = +1400V electric field map

Fig.20



CE2 = -1400V electric field map

Fig. 21

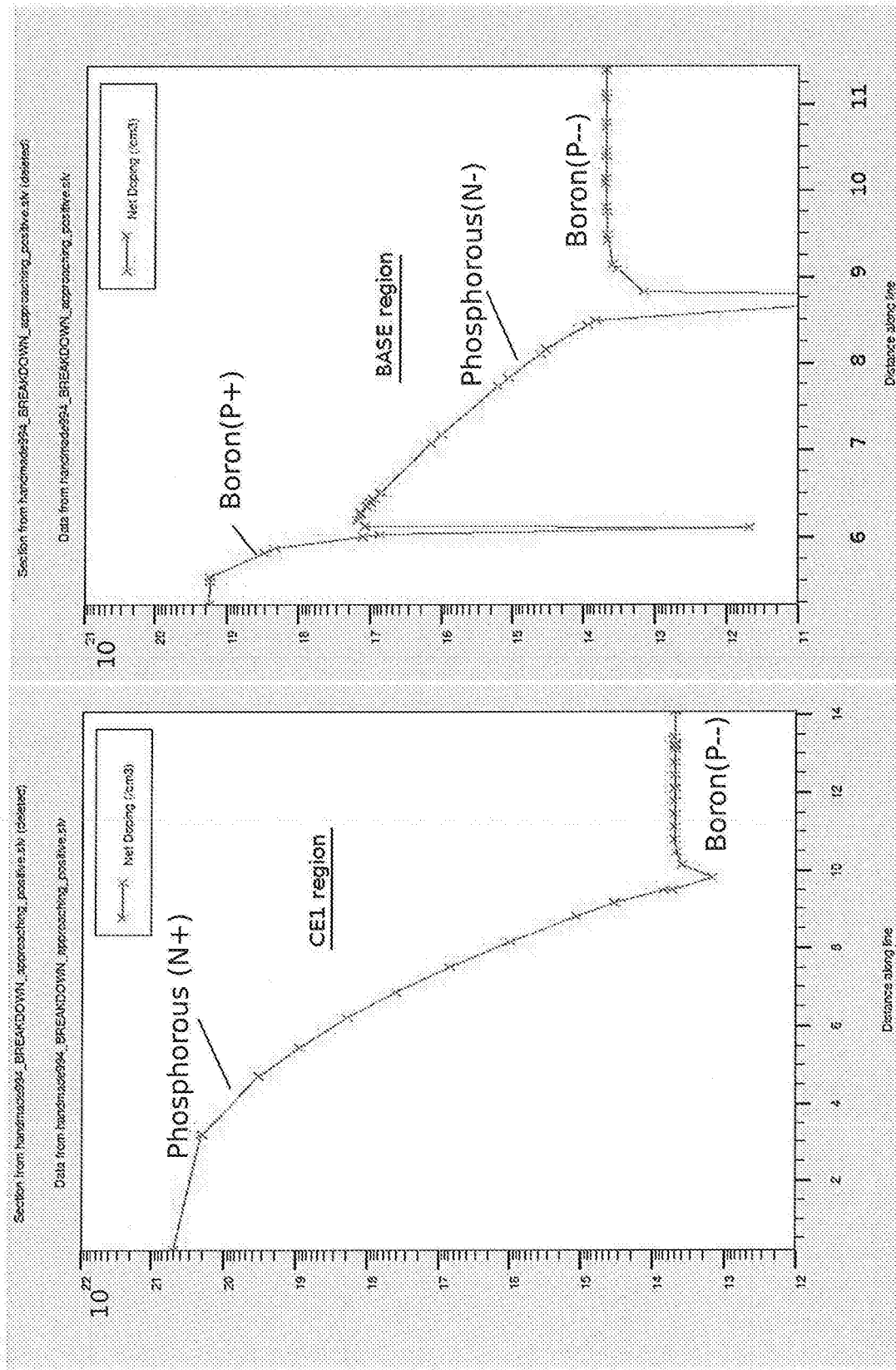
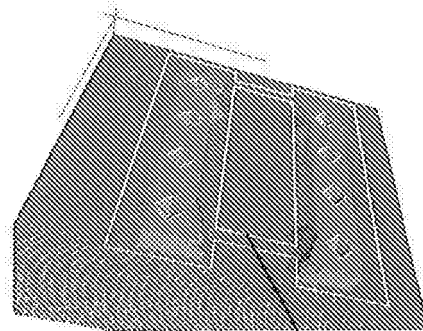
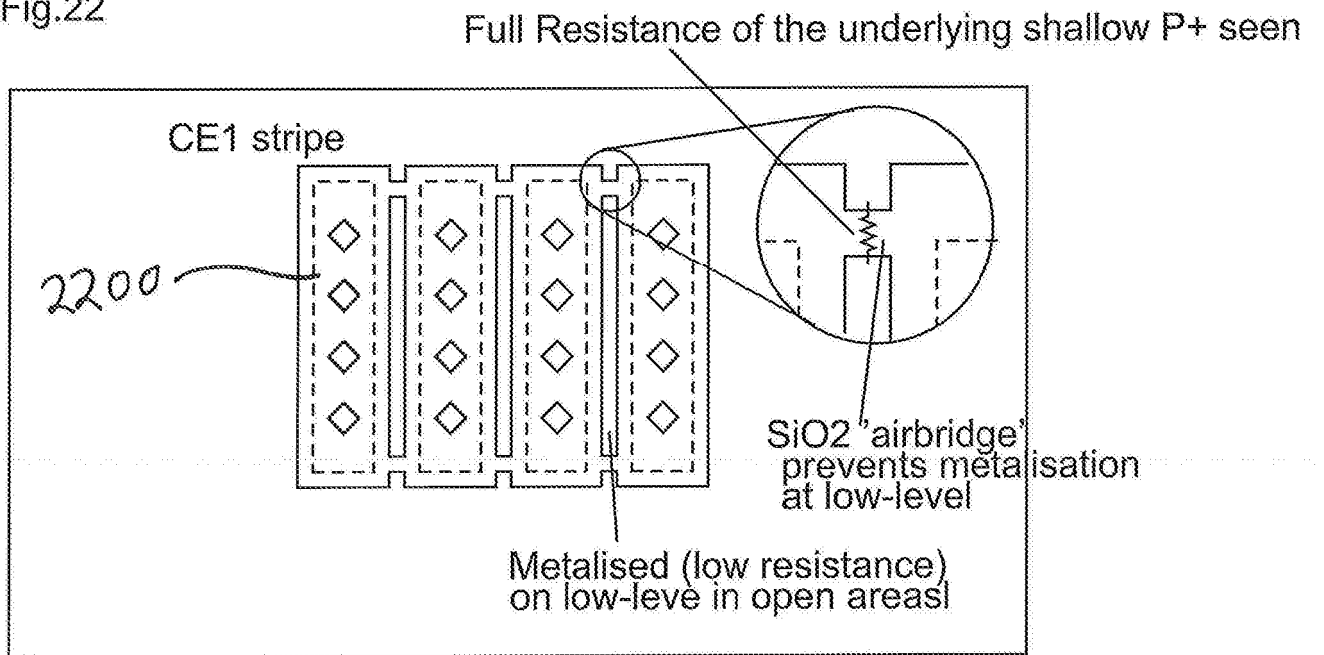


Fig.22



Etch simulator result of section

SiO₂ 'air-bridge' where silicon completely etched away underneath

Fig.23

Solid-state relay module including a 'slab' type inductor for bootstrap DCDC

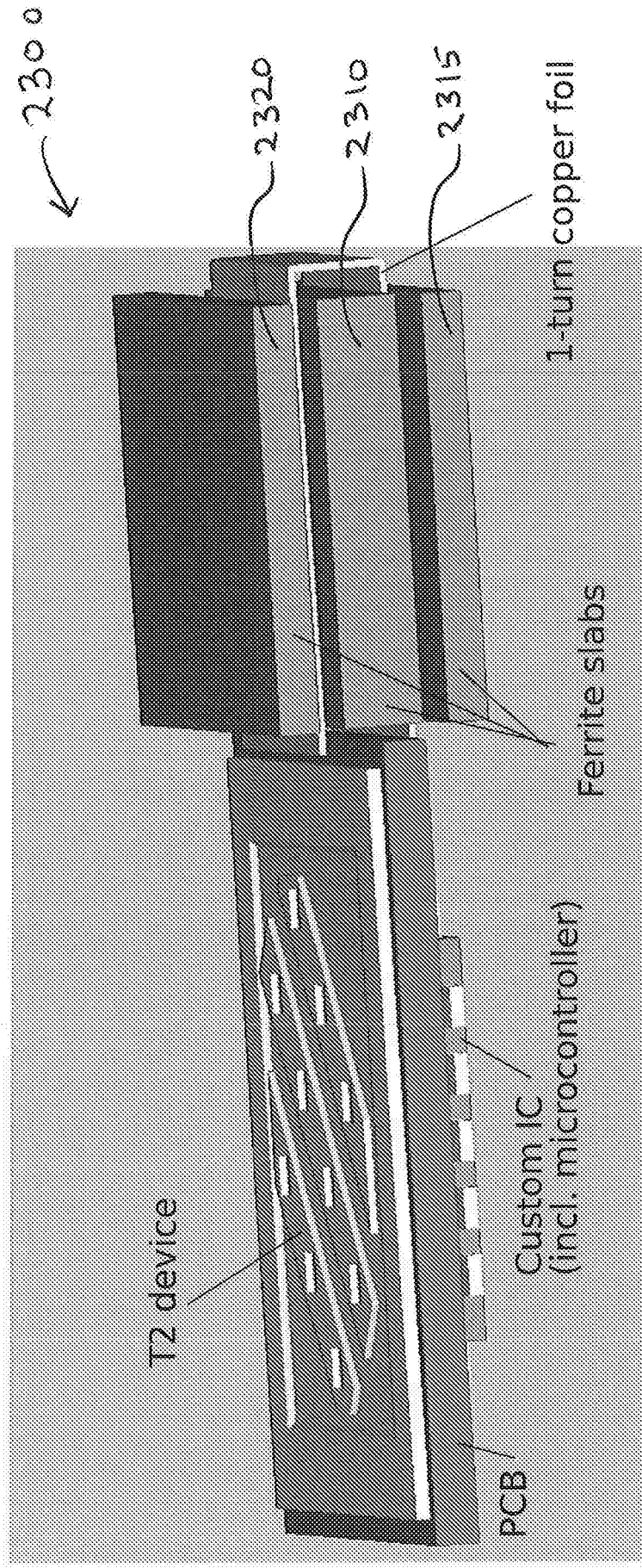


Fig24 A) BJT BASE: DEVICE IS OFF

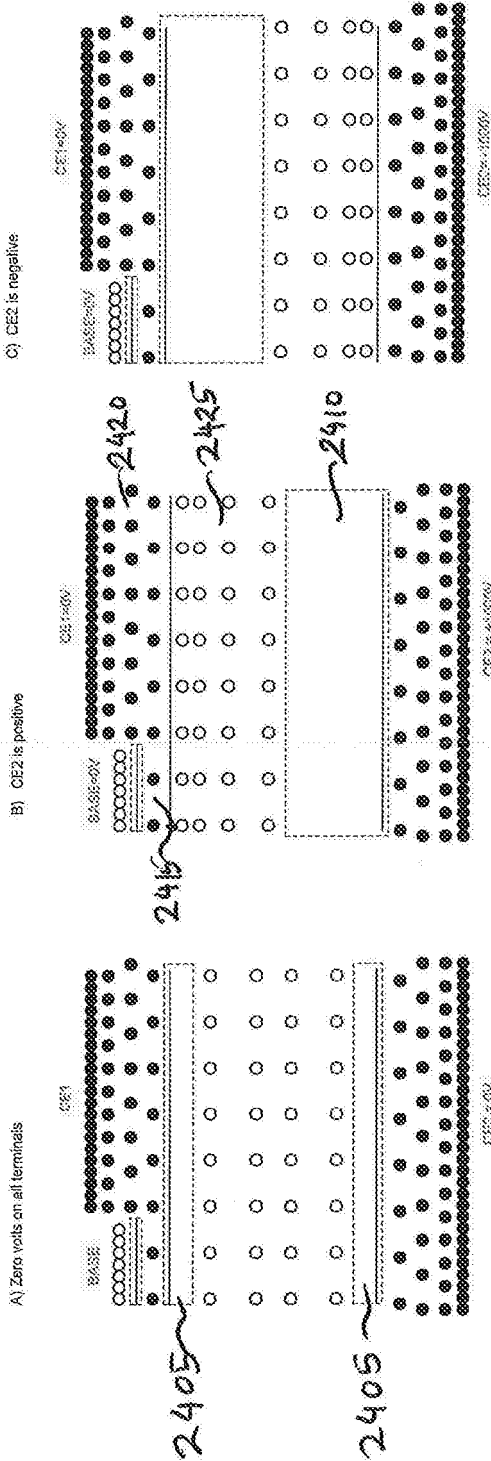
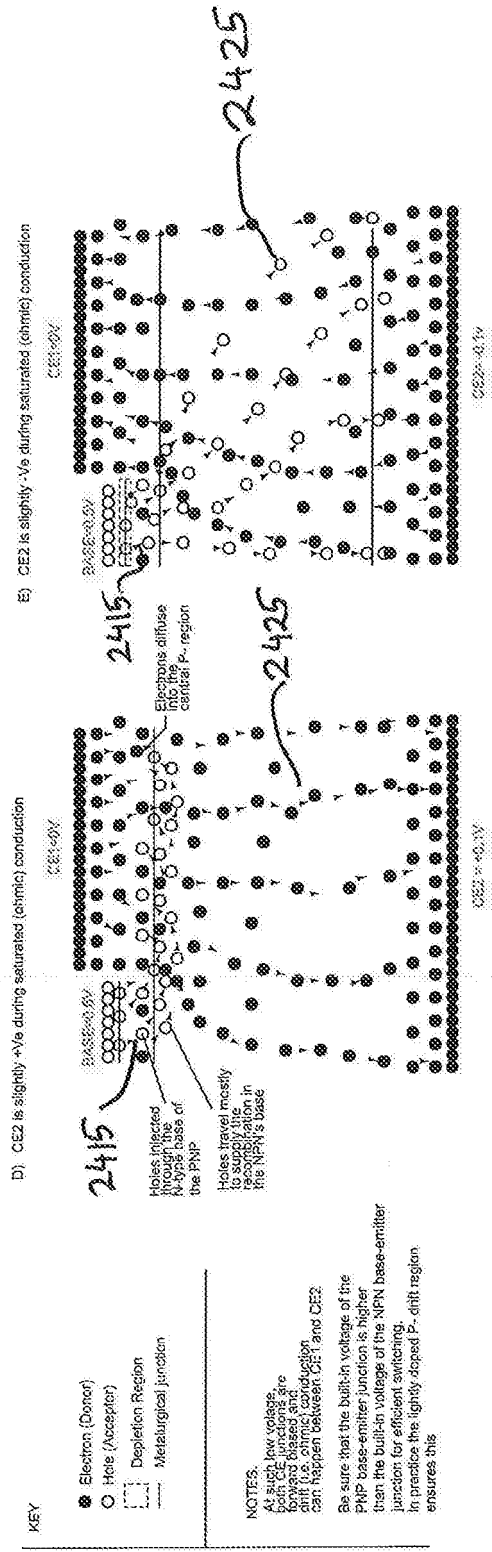


Fig24 B) BJT BASE: DEVICE IS ON



KEY

- Electron (Donor)
- Hole (Acceptor)
- Depletion Region
- ▭ Metallurgical Junction

NOTES

At such low voltage, the built-in junctions are forward biased and drift (i.e. ohmic) conduction can happen between CE1 and CE2. Be sure that the built-in voltage of the PNP base-emitter junction is higher than the built-in voltage of the NPN base-emitter junction for efficient switching. In practice the lightly doped P₊-drift region ensures this.

Fig25 A) JFET BASE - DEVICE IS OFF

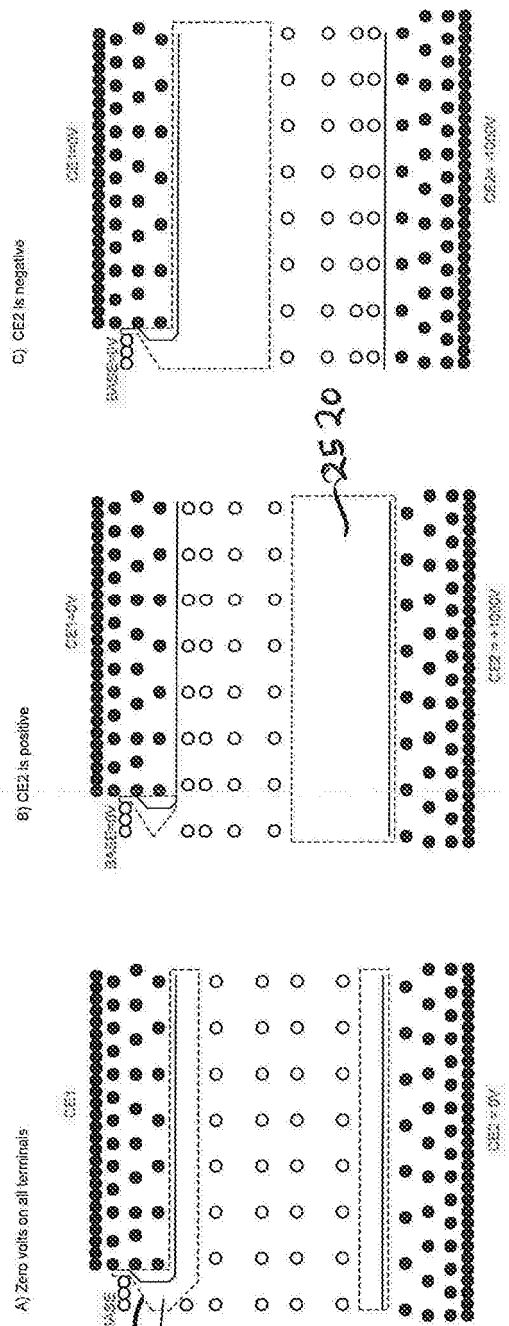


Fig25 B) JFET-BASE - DEVICE IS ON

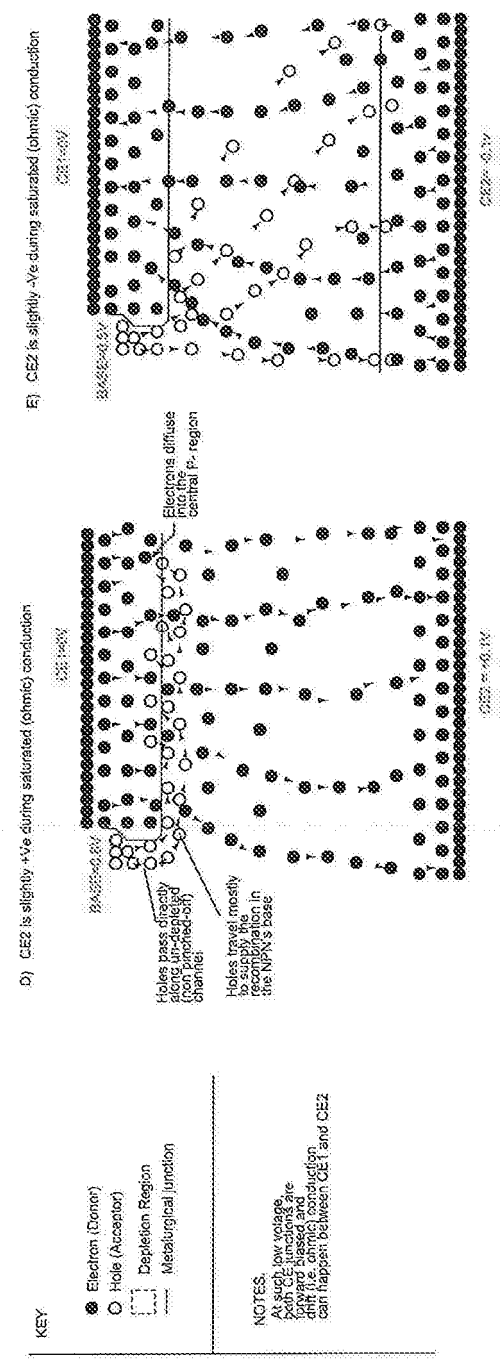
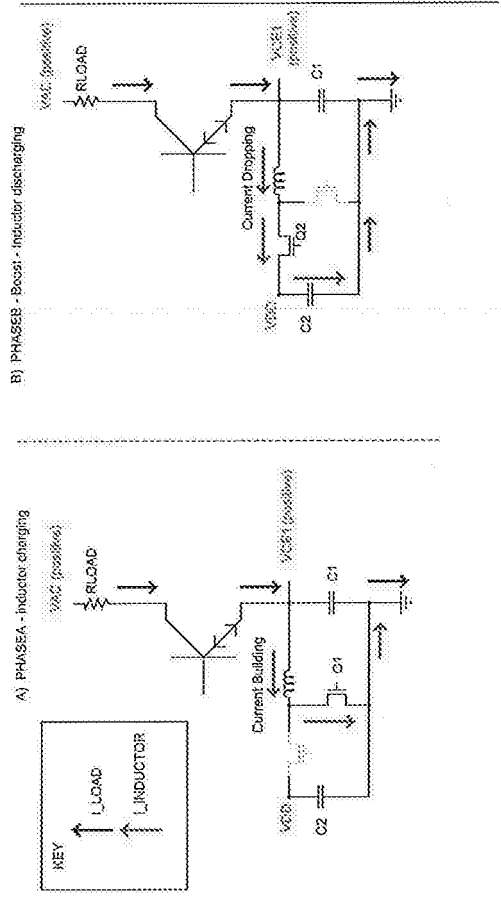


Fig26 Bootstrap, Chargepumps and Base drive circuits

POSITIVE OPERATION



NEGATIVE OPERATION

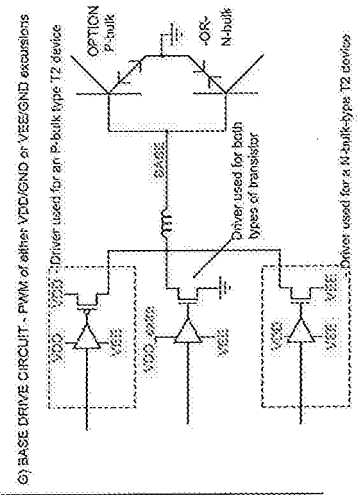
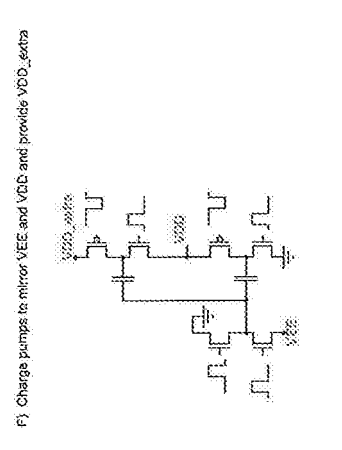
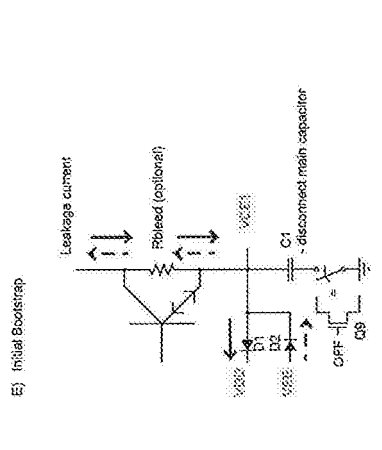
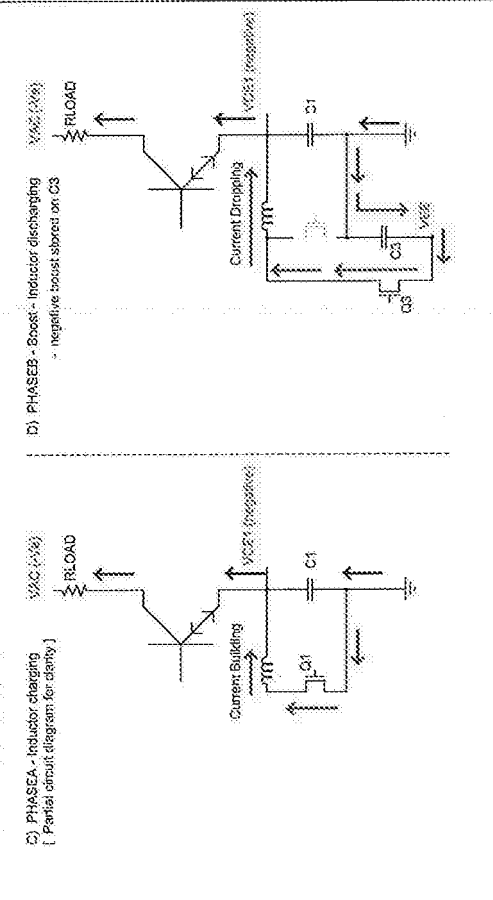
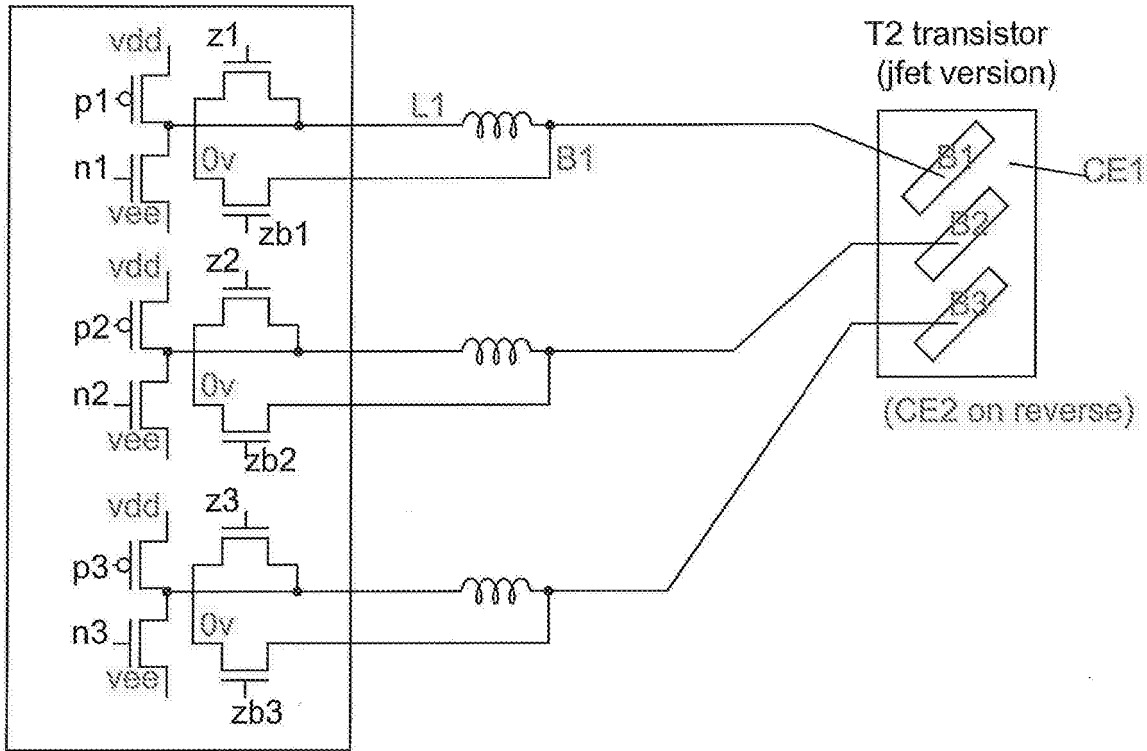


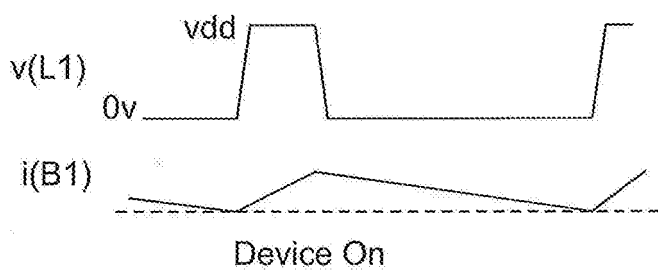
Fig27

A) Multi-output inductive base drive

Multiple base stripes

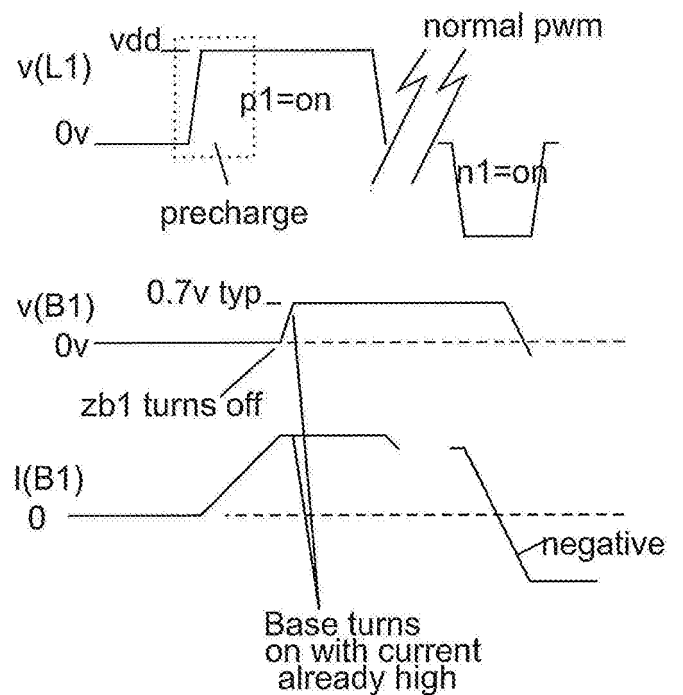


B) example voltage waveforms (repeating)



L2,B2, and L3,B3 are phase-shifted versions of above, moved by 120 degrees

C) base pulse using precharge and discharge



Base 'Finger' driver - one channel

- for PNP based devices (-ve base current)

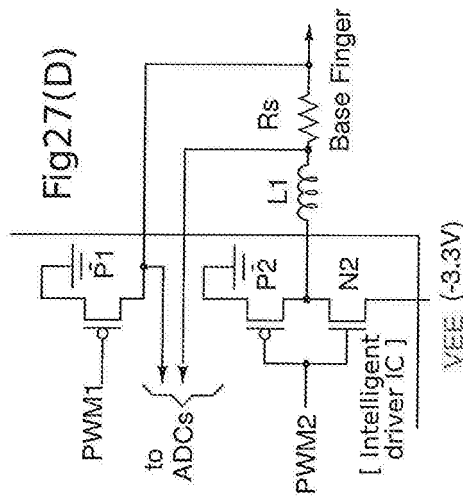


Fig27(D)

- for NPN based devices (+ve base current)

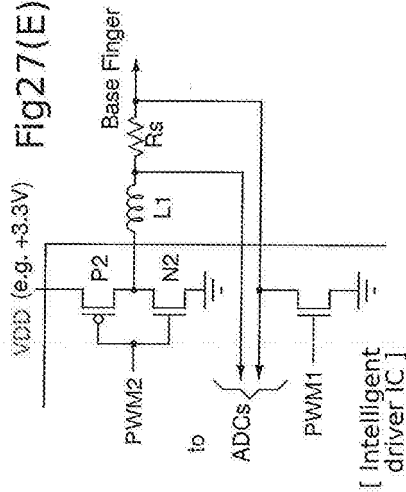


Fig27(E)

Multiphase operation single-base connection

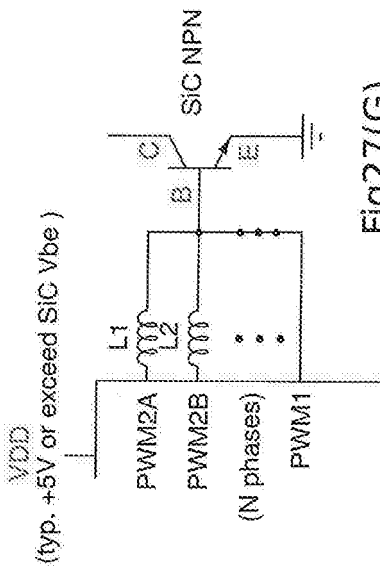


Fig27(G)

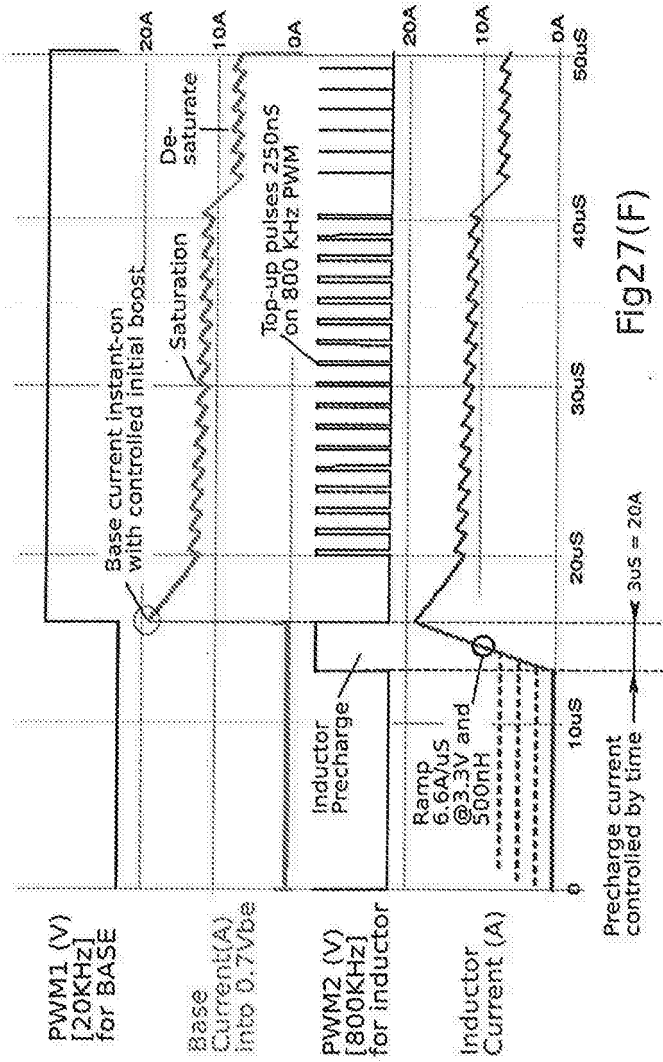


Fig27(F)

BASE On/Off controlled by PWM1

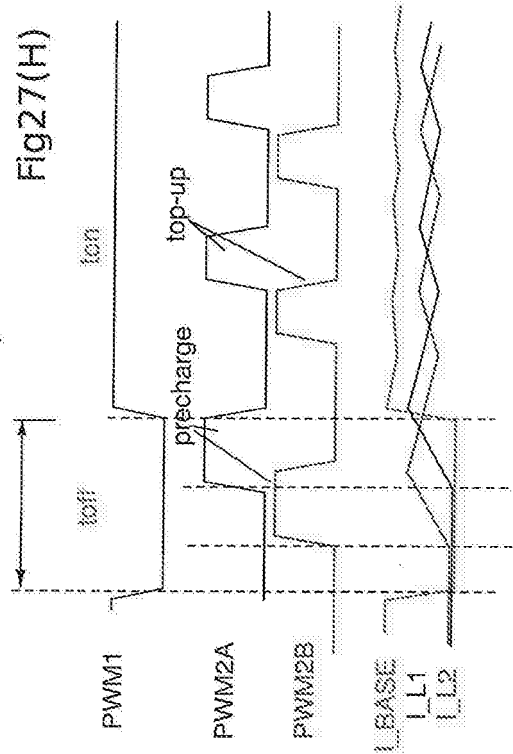


Fig27(H)

Fig28

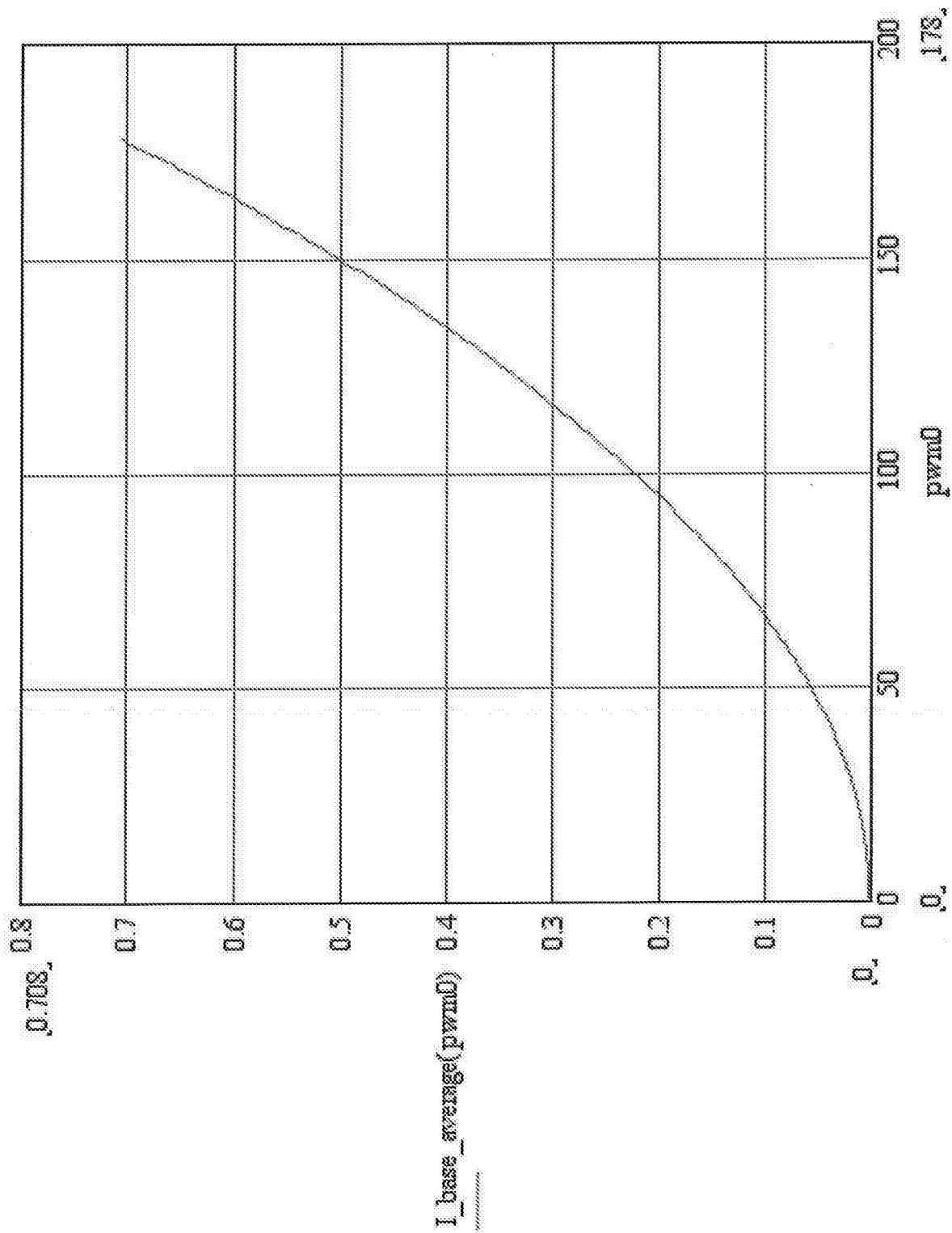


Fig.29 - Programable DAC base drivers - multi-channel

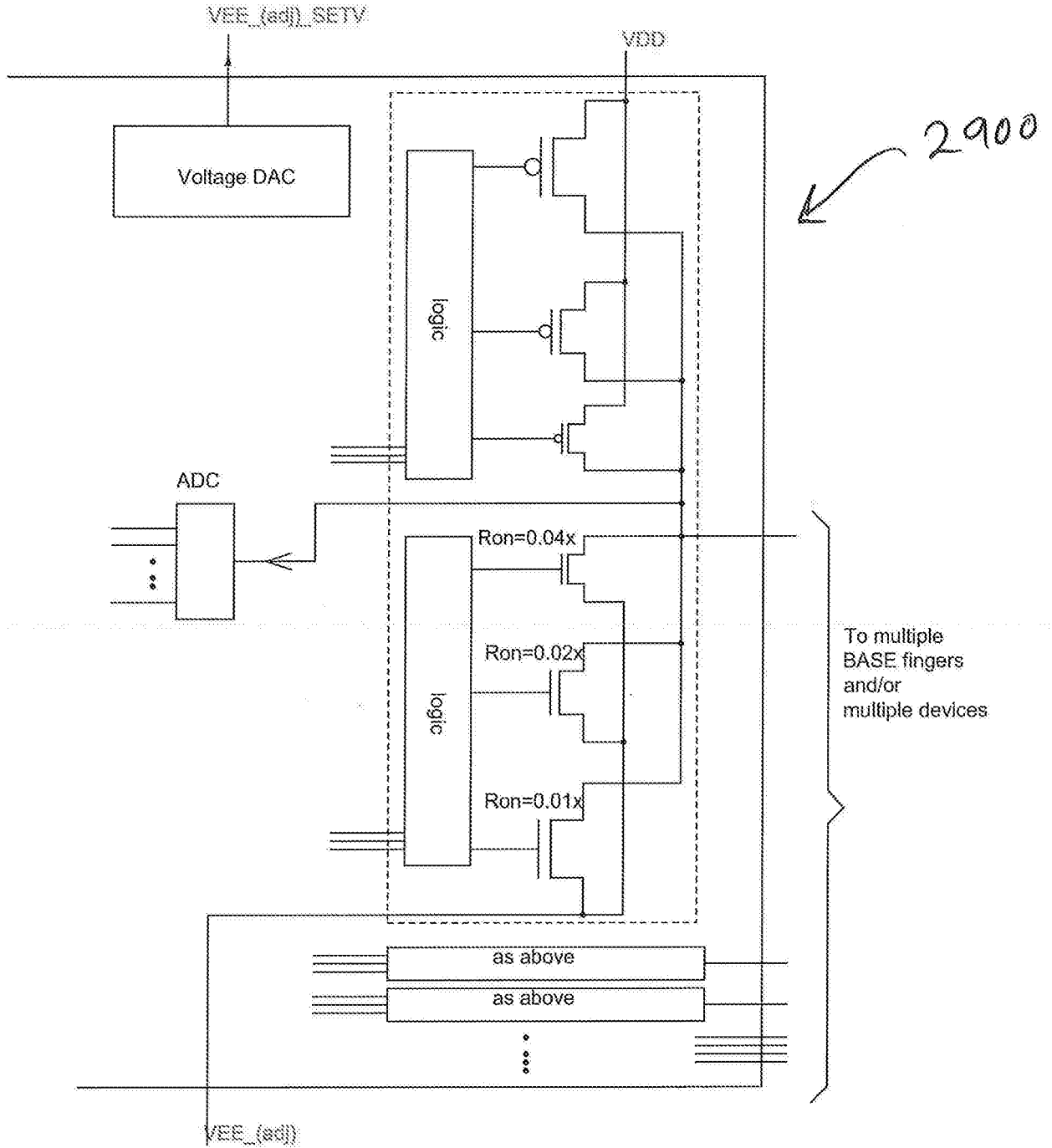
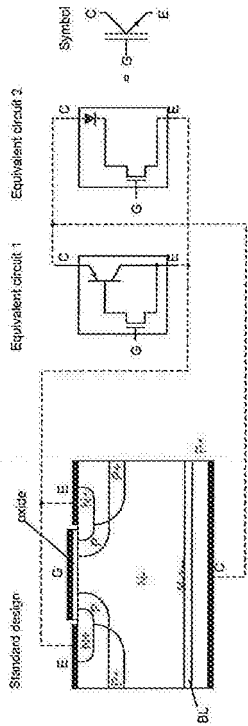
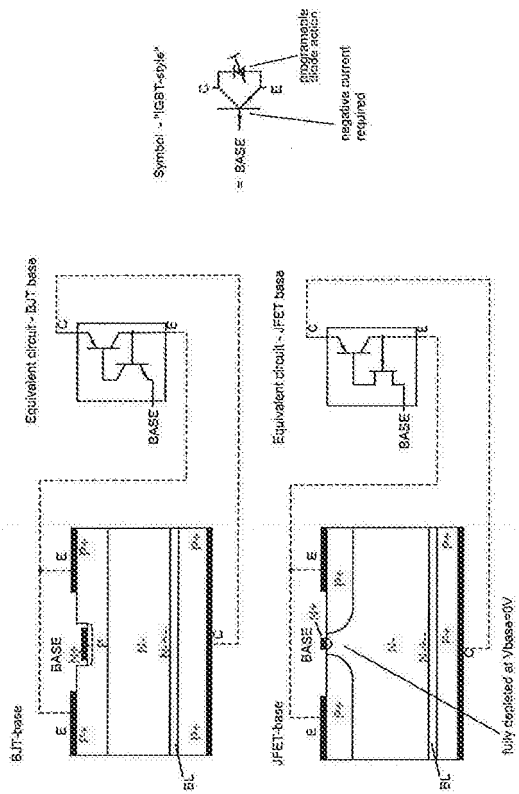


Fig. 30

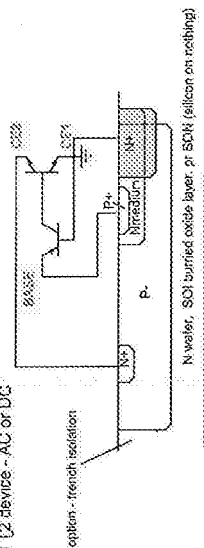
A) IGBT



B) I2 device "NIGBT" - AC or DC

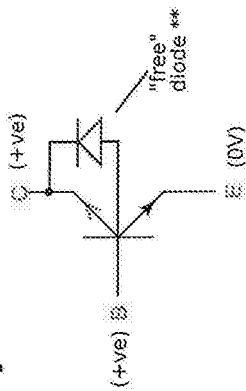


(C) Lateral I2 device - AC or DC

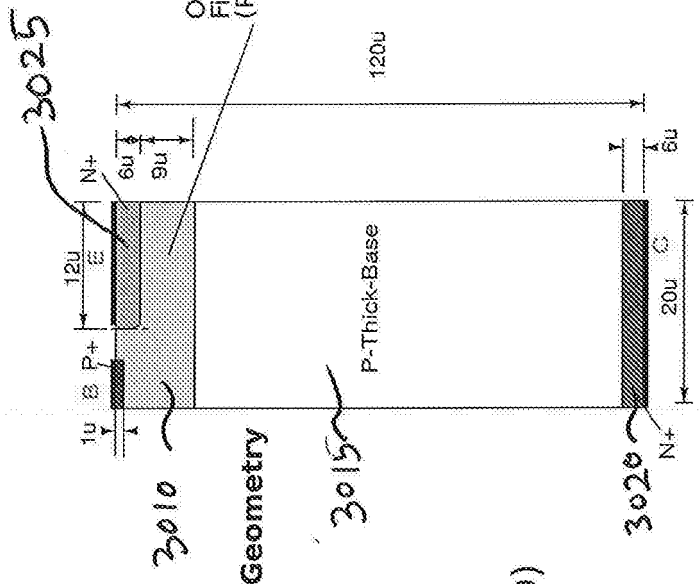


B2 device BJT NPN Field-Stop

Symbol



** when used with CMOS driver



Geometry

Fig30(D)

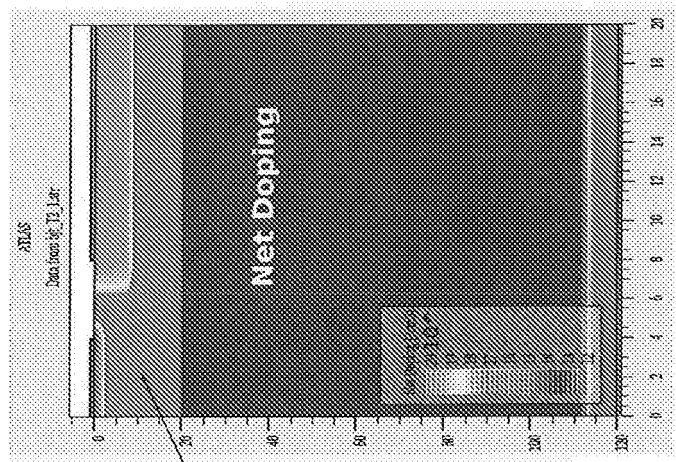


Fig30(E)

Beta vs. Current Density at Vce(sat) = 0.2V

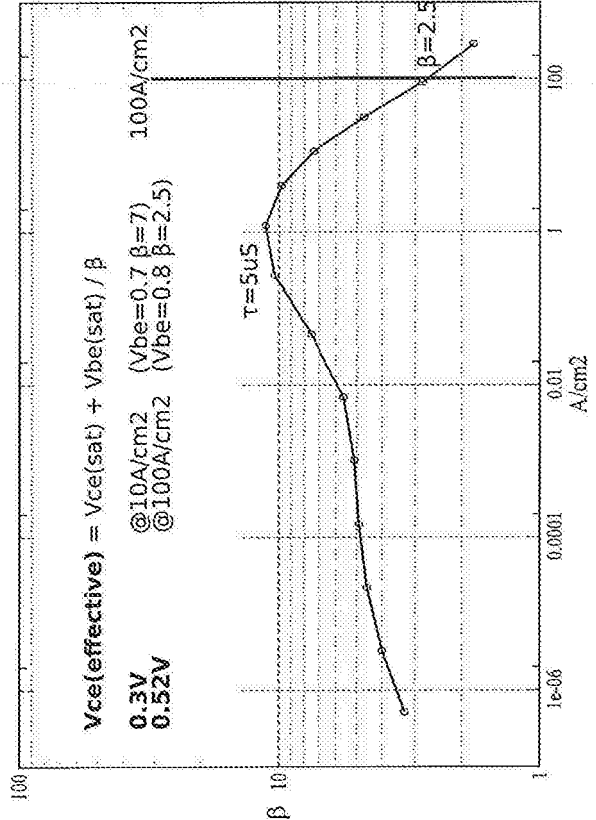


Fig30(F)

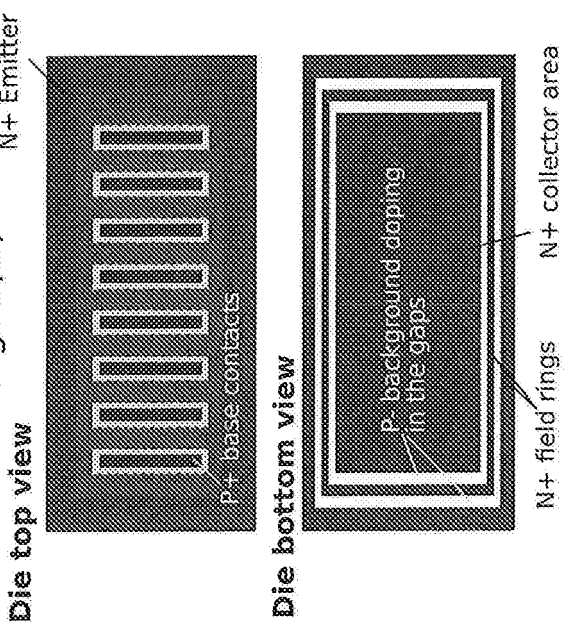
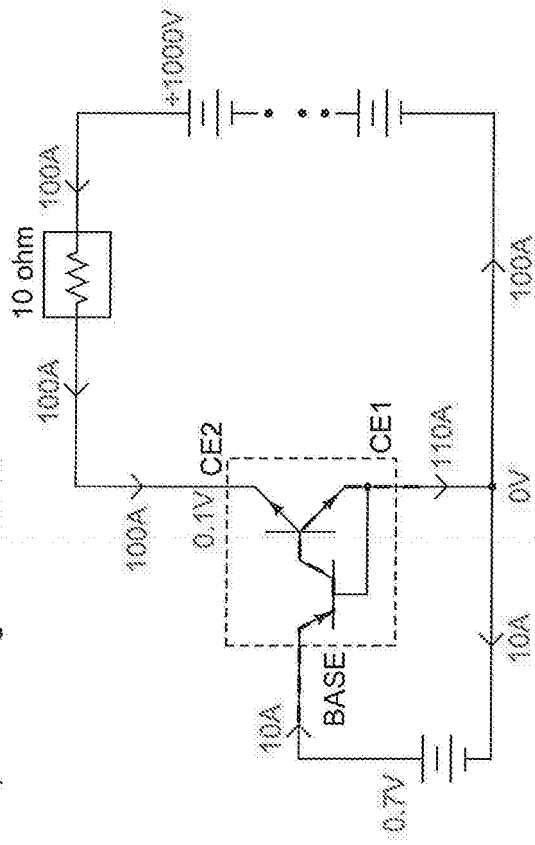


Fig30(G)

Fig.31

A) Conducting a +Ve current



B) Conducting a -Ve current

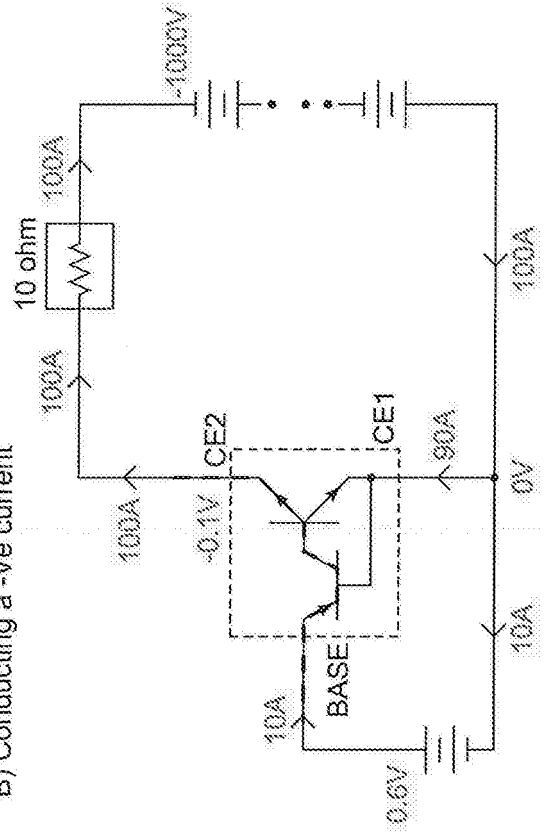
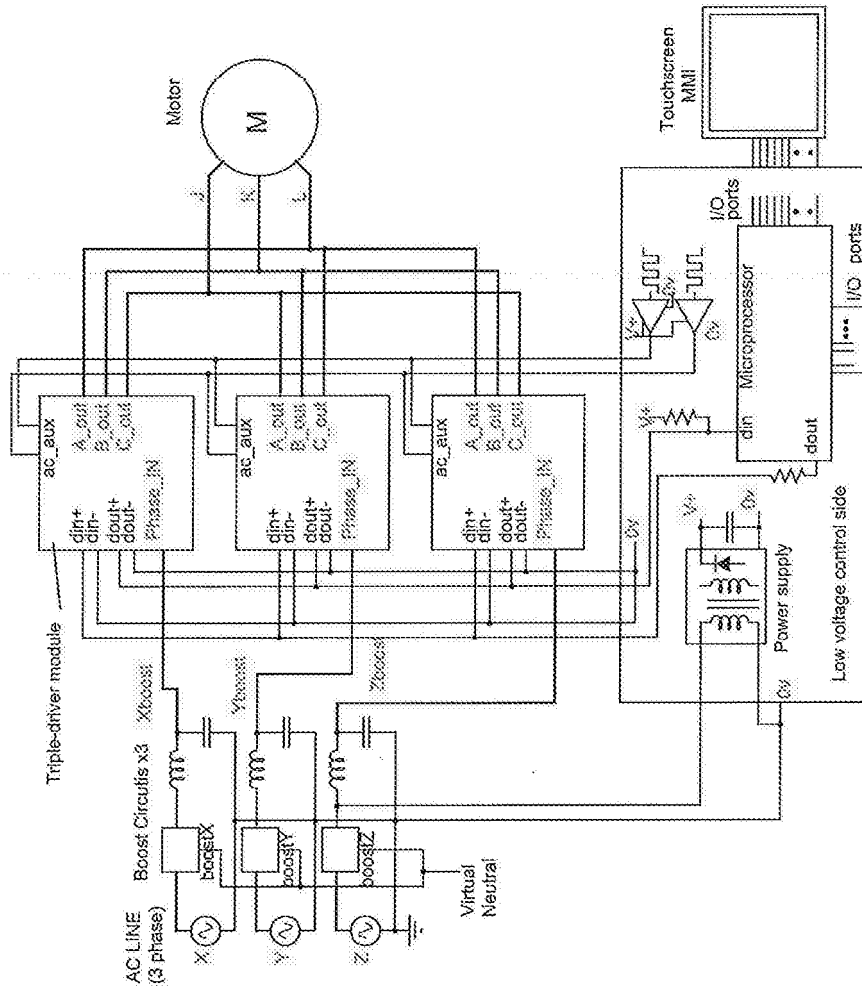
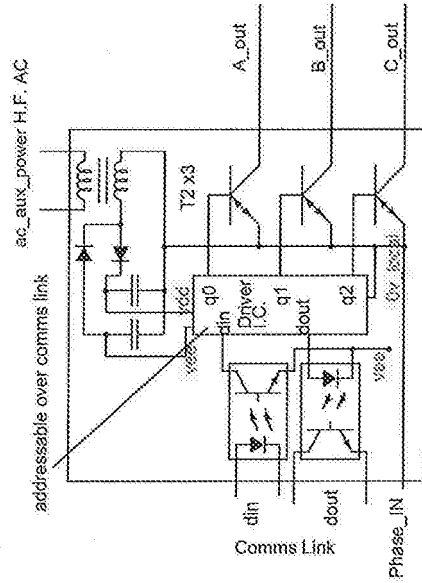


FIG32

A) VARIABLE FREQUENCY MATRIX-CONVERTER DRIVE SYSTEM



B) TRIPLE DRIVER MODULE - Internals



Simplified internals diagram of triple-T2 driver module
 - not shown are A-D, D-A I/O, Microcontroller features which were previously shown on single-channel drivers and can obviously be applied here to all 3 switches

C) BOOST CIRCUIT (AC/AC transformer - concept drawing)

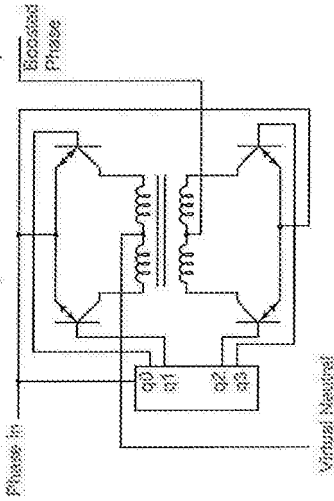


FIG 33(A) 3D stack for Driver IC, Discretes and Power transistor for integrated-driver module

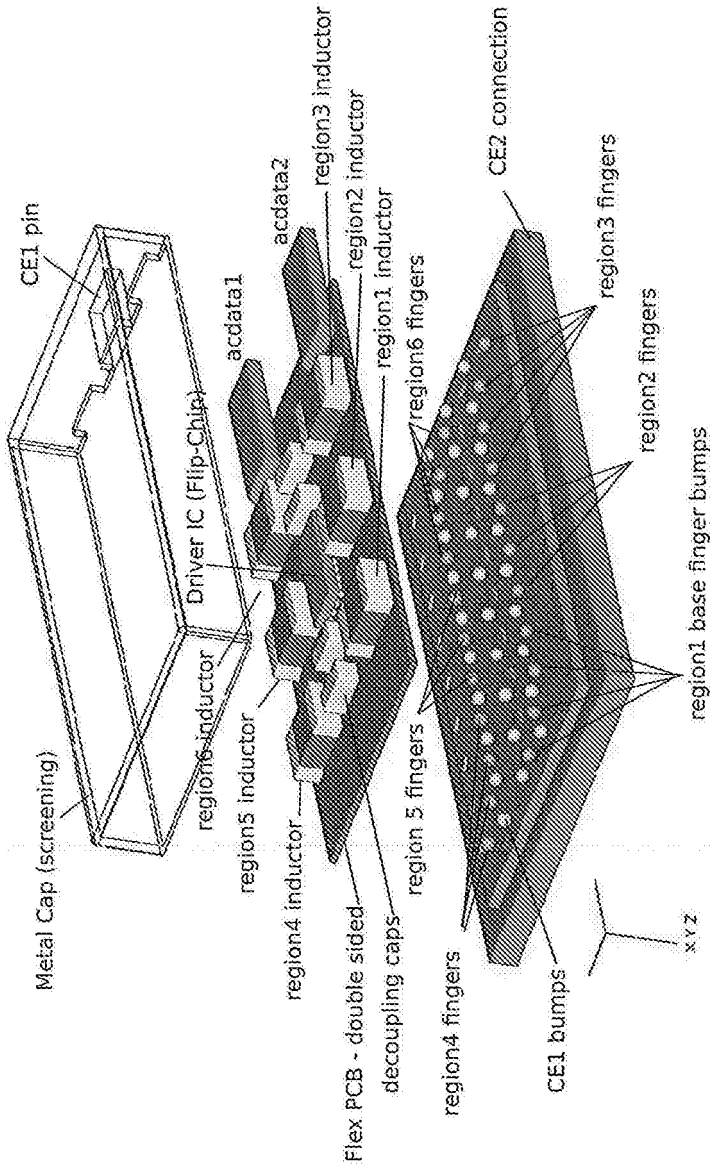


FIG 33(B)

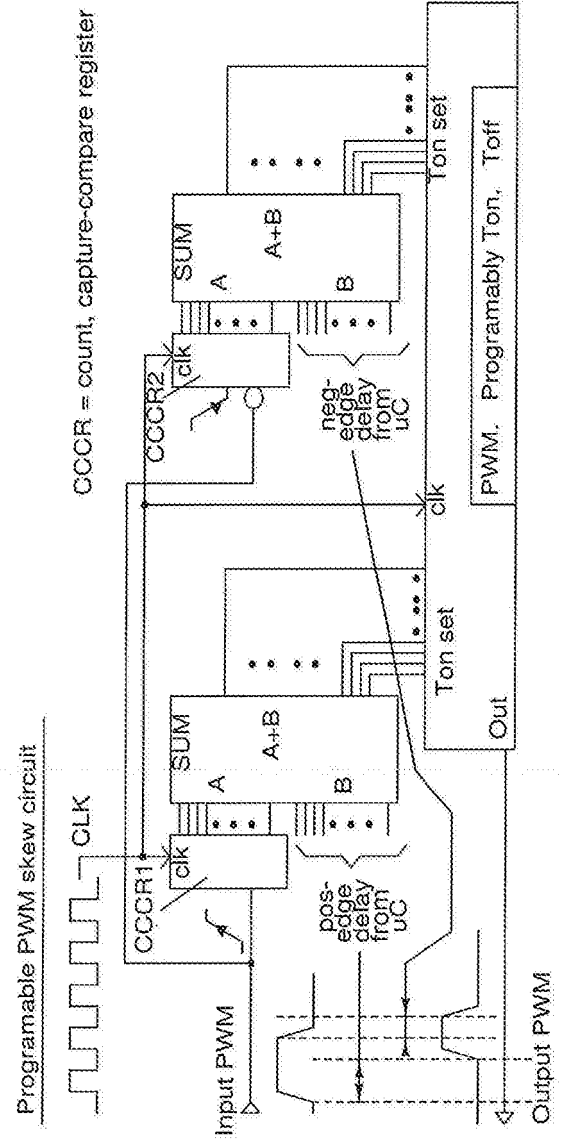


Fig 34 - low leakage relay switches

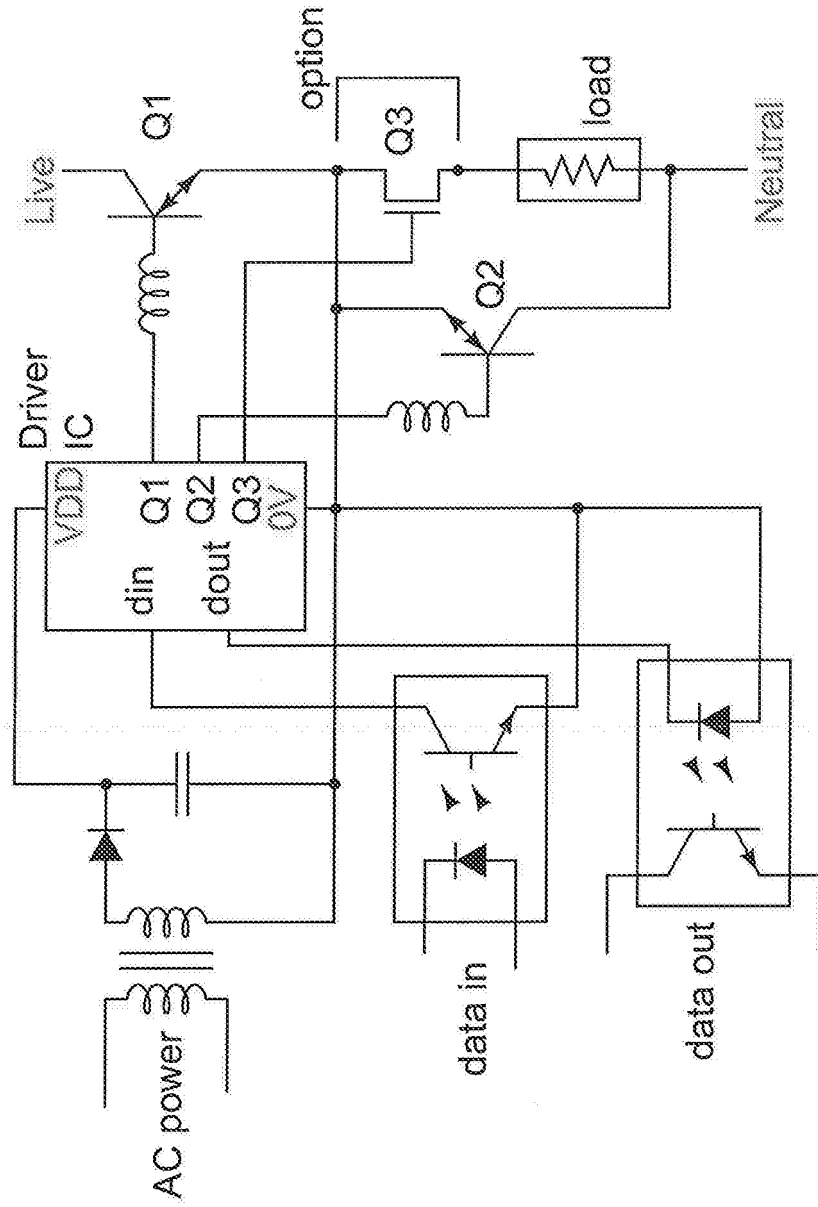


Fig35A NMOS vertical conduction on modified CMOS

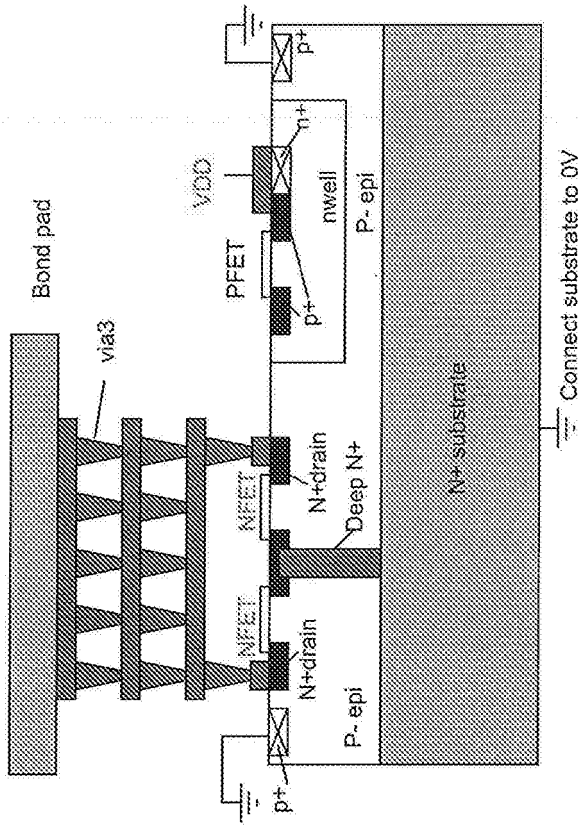


Fig35B Synchronous rectifier from transformer with 2-way dataflow

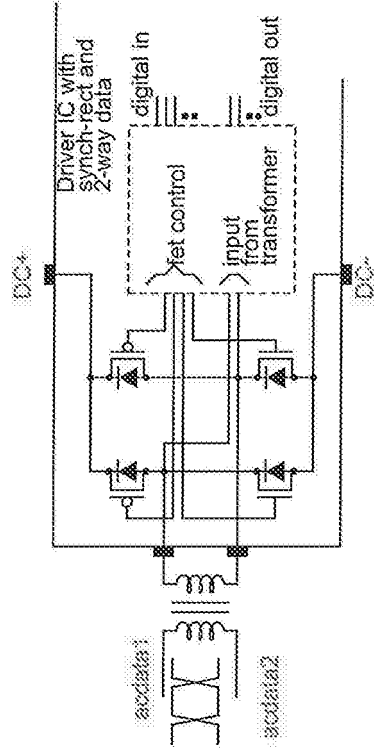
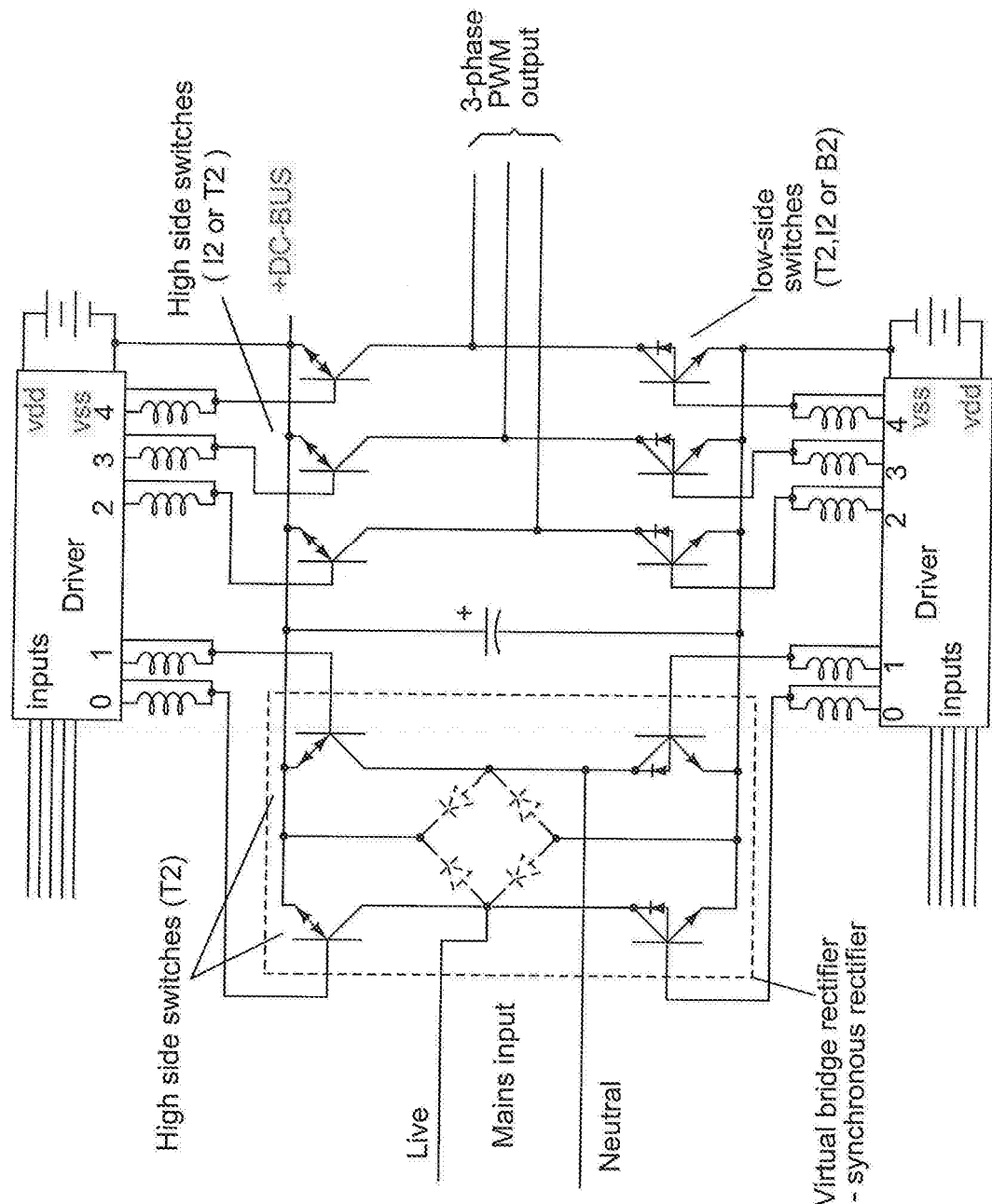


Fig. 36 - Efficient 3-phase inverter using DC bus, synchronous mains rectification



Note: Input level translators not shown. Aux. power supplies (Vdd/Vss) shown simplified